

## Lab Training Session: Solid State Detectors

# Introduction to Silicon Detectors for the LHC *and Radiation Damage to Silicon Detectors*

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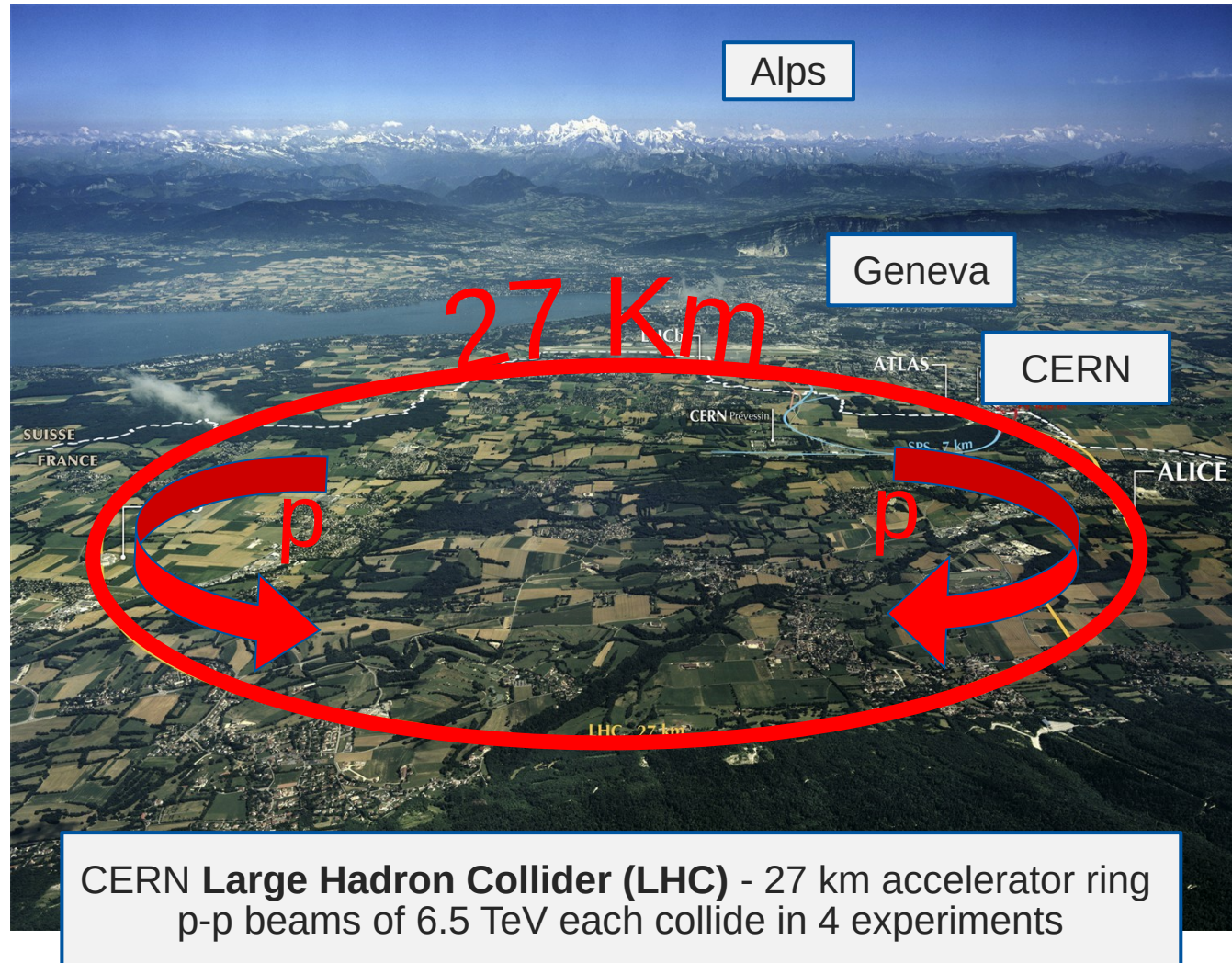
**Solid State Detectors (SSD) laboratory,  
CERN EP-DT, Geneva, Switzerland**

*\*Slides prepared by Michael Moll*

- **The Large Hadron Collider (LHC) at CERN**
  - Where are the silicon detectors?
- **Silicon Detectors for High Energy Physics Applications**
  - The basic concept of Semiconductor Detectors: A reverse biased pn-junction
  - Strip and Pixel Detectors at the Large Hadron Collider (LHC) at CERN
  - *Some recent developments in Silicon Detectors*
- **Radiation Damage to Silicon Detectors**
  - Upgrade of the Large Hadron Collider (HL-LHC)
  - Radiation damage mechanisms
  - *Mitigation techniques: What can we do against radiation damage?*
- **Characterization techniques for silicon sensors**
  - **Current-Voltage (IV) and Capacitance-Voltage (CV) measurements**
  - **Laser based measurements: Transient Current Technique (TCT)**
- **Summary & Further reading**



Lab Training  
Session



- **CERN:**

- 23 member states
- ~14000 scientists (Users)
- ~ 2600 personnel
- Budget ~1200 MCHF

- **LHC: 27 km tunnel**

- 4000 MCHF (machine+experiments)
- 1232 dipoles  $B=8.3T$
- Design:  $pp \quad s = 14 \text{ TeV}$   
 $L_{\text{design}} = 10^{34} \text{ cm}^{-2} \text{ s}^{-1}$   
Heavy ions (e.g. Pb-Pb; 5TeV)

- **Circulating beams:**

2008: first beam

2012: Run 1 at 2 x 4 TeV (Higgs boson)

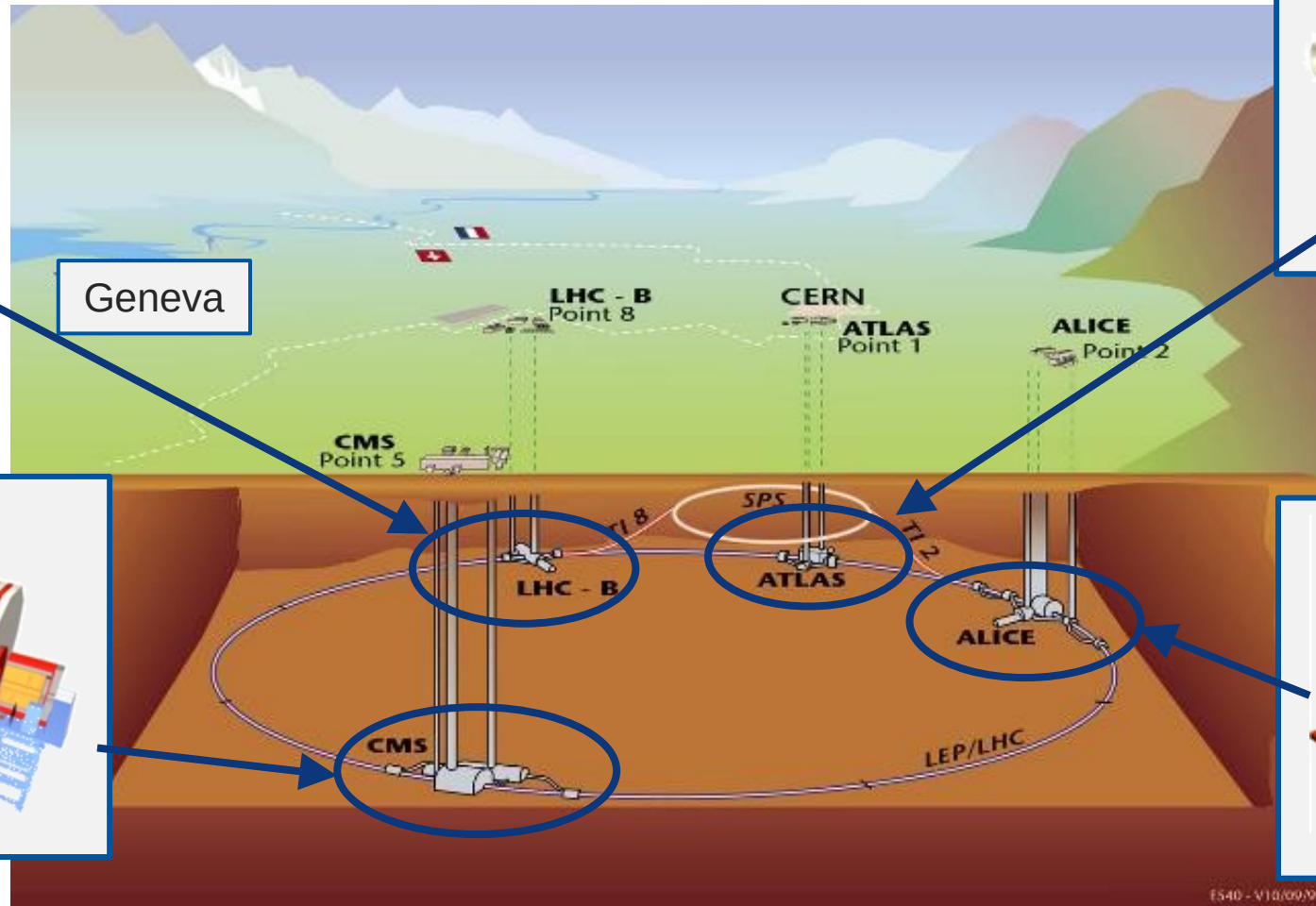
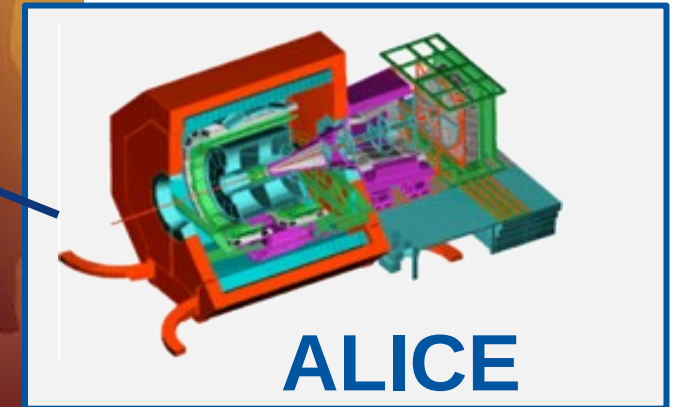
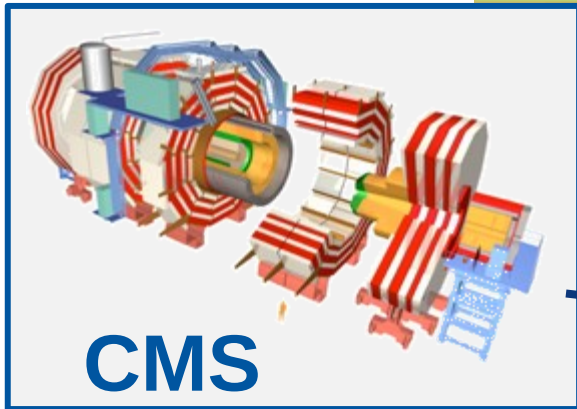
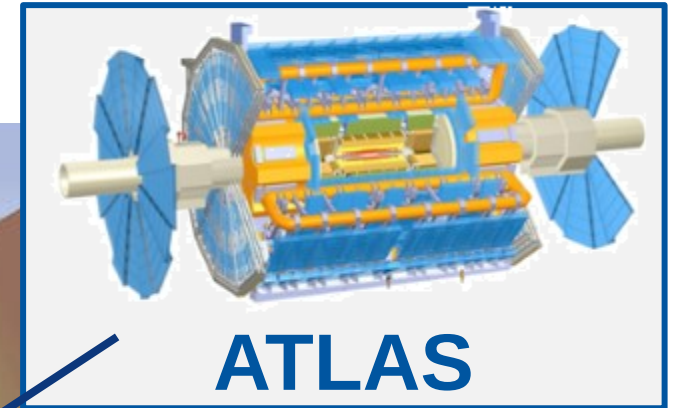
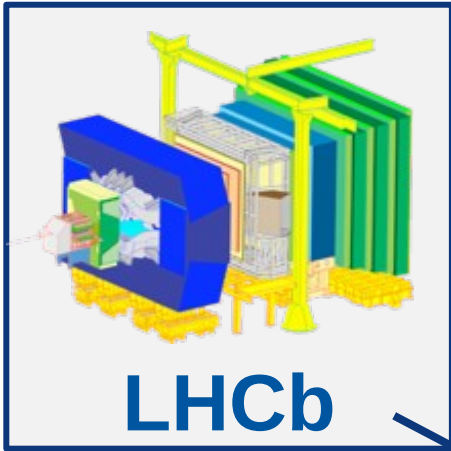
2015: Run 2 at 2 x 6.5 TeV

2016: Reaching  $10^{34} \text{ cm}^{-2} \text{ s}^{-1}$

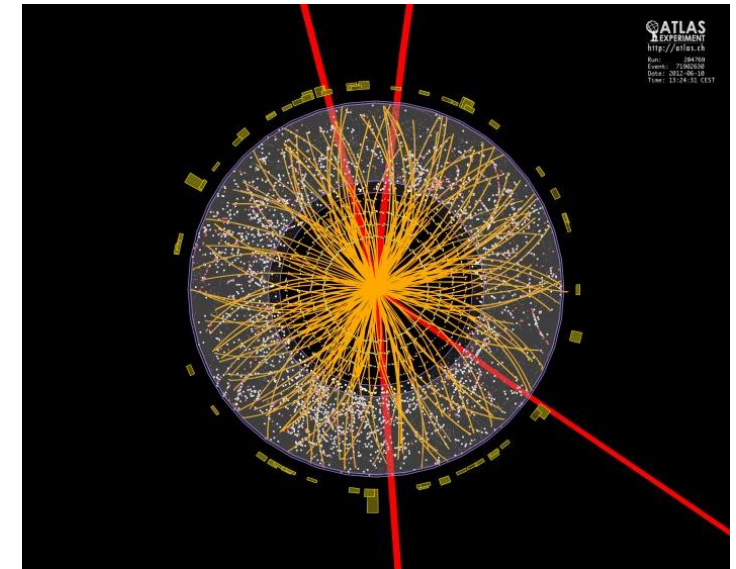
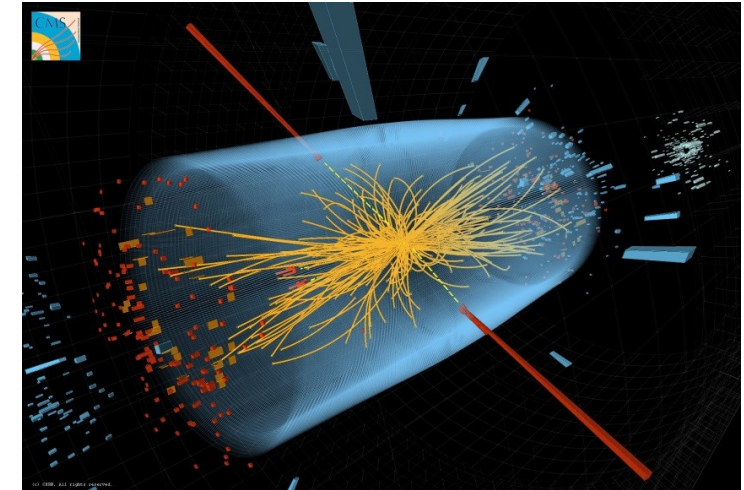
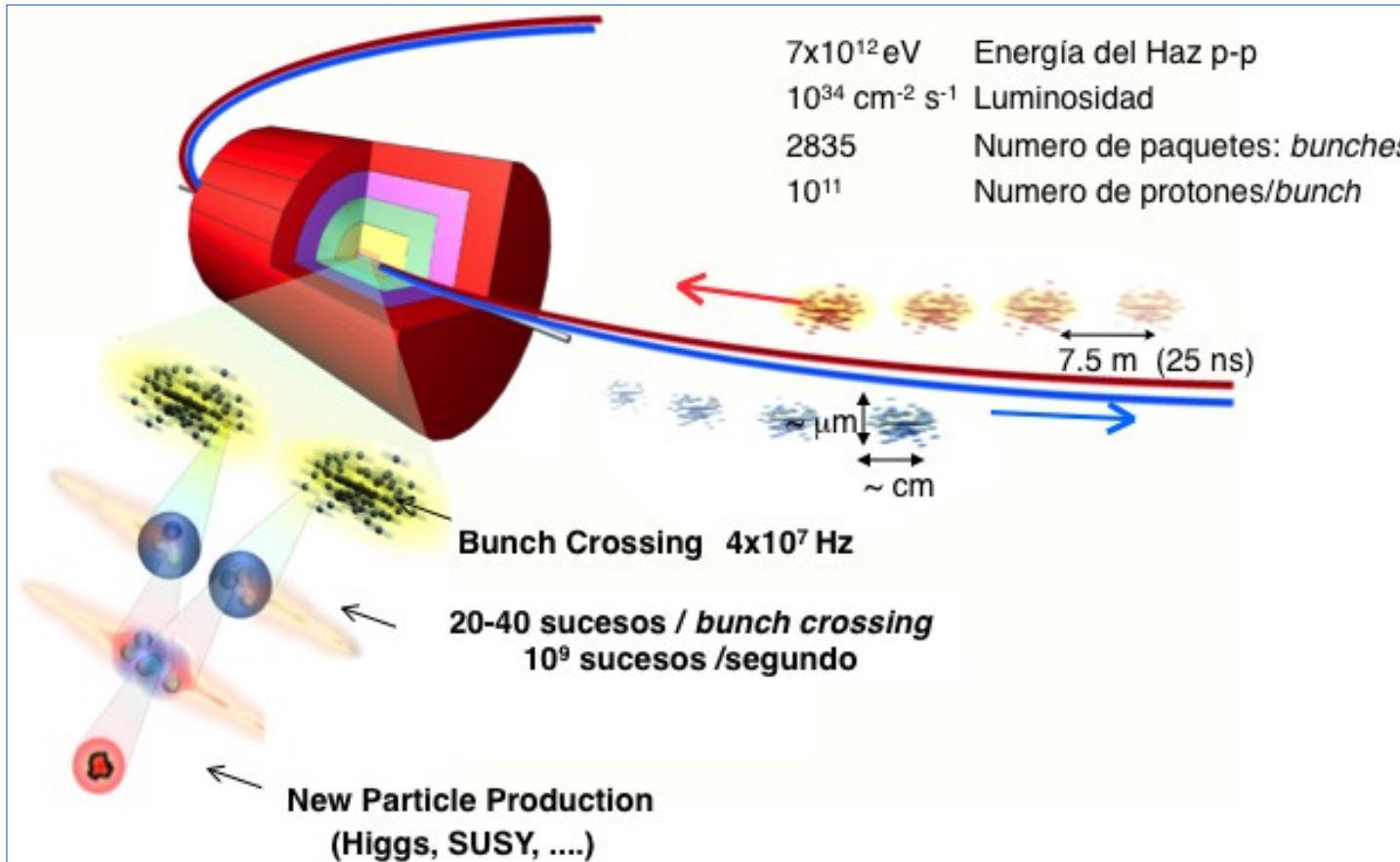
2018: LS2; 2022: Run 3

2026: LS3; **2029: HL-LHC**

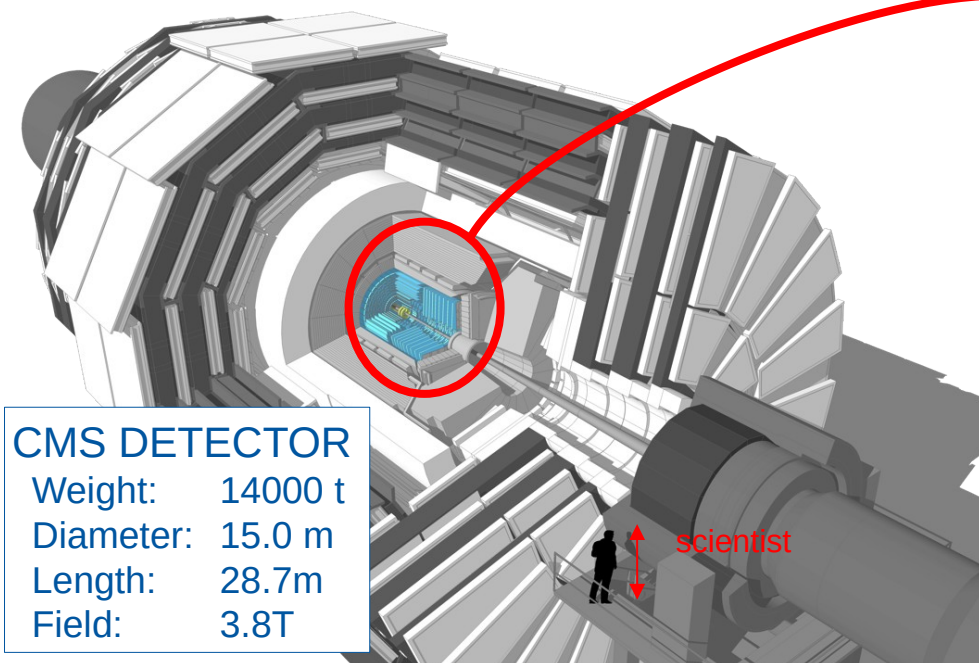
# The LHC Experiments



# Collisions in the LHC



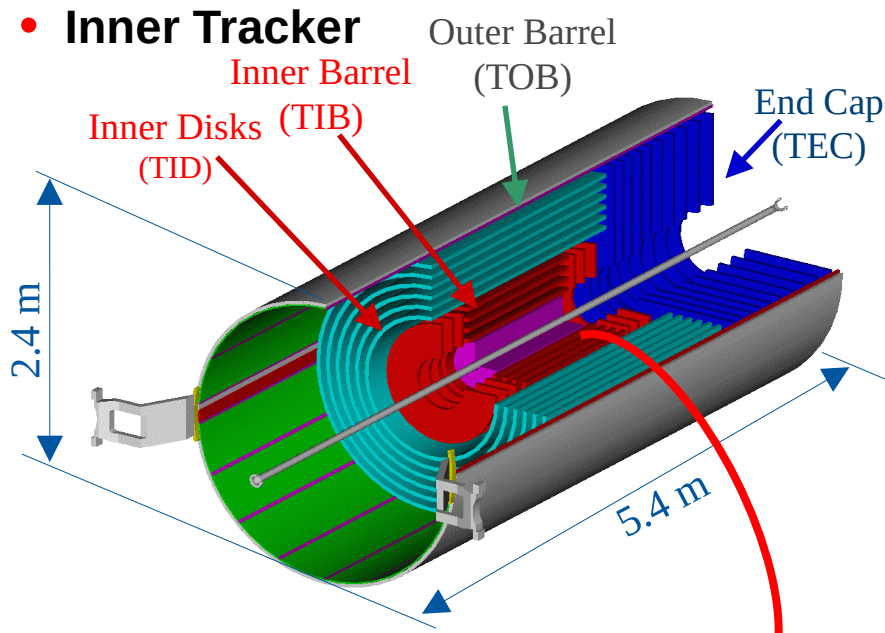
- LHC example: The CMS DETECTOR



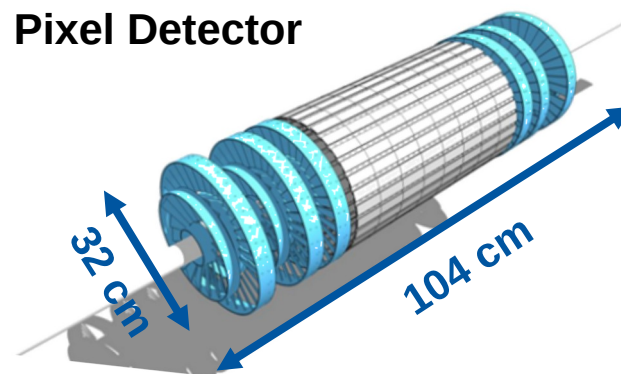
**CMS DETECTOR**  
 Weight: 14000 t  
 Diameter: 15.0 m  
 Length: 28.7m  
 Field: 3.8T

- CMS – Inner Tracker & Pixel Detector

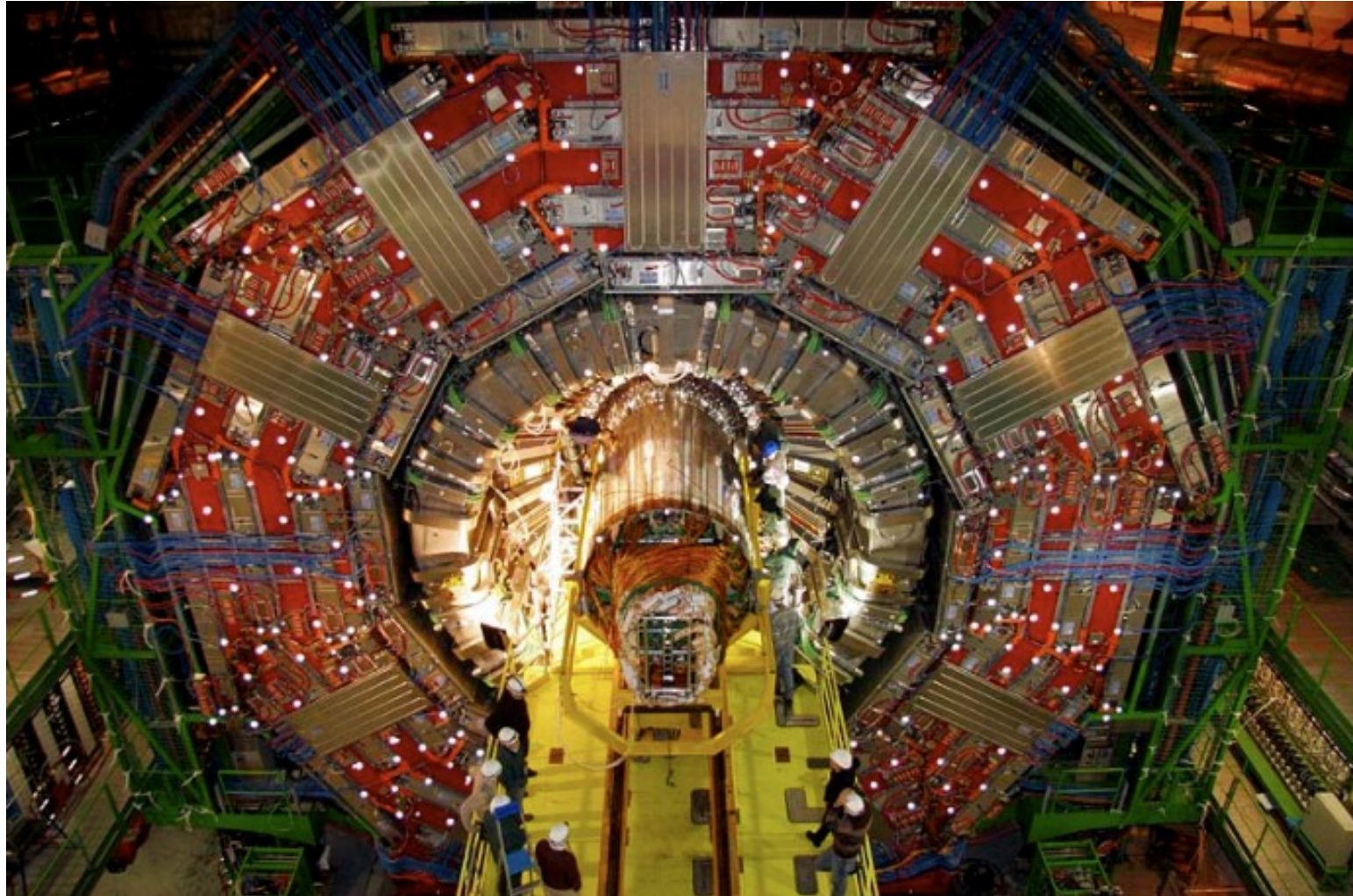
- **Micro Strip:**
  - ~ 214 m<sup>2</sup> of silicon strip sensors, 11.4 million strips
- **Pixel:**
  - 4 layers & 2 x 3 disks: silicon pixels (~ 1m<sup>2</sup>)
  - 124 million pixels (100x150μm<sup>2</sup>)
  - Resolution:  $\sigma(r\phi) \sim 10 \mu\text{m}$ ,  $\sigma(z) \sim 25\mu\text{m}$



- Pixel Detector



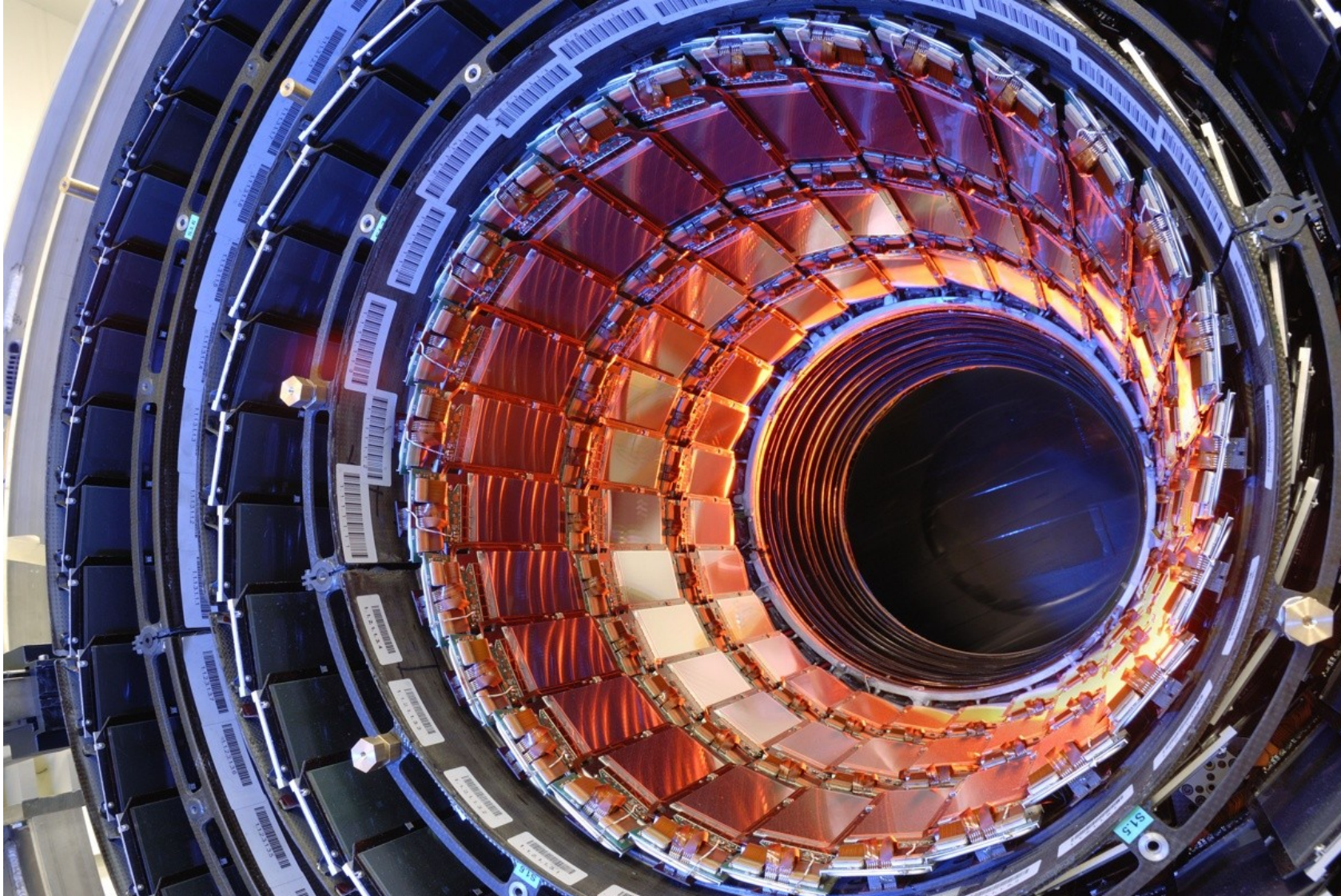
# Present LHC Tracking Sensors



CMS Tracker insertion

December 2007

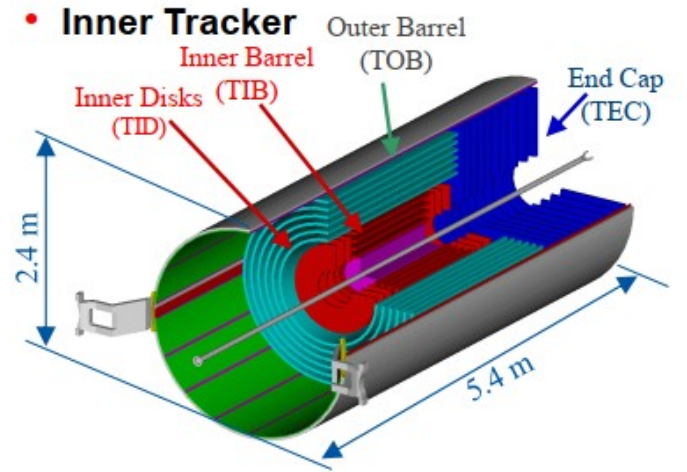
# Present LHC Tracking Sensors



M.Krammer, ICFA School, Bogota, 2013

January / February 2023

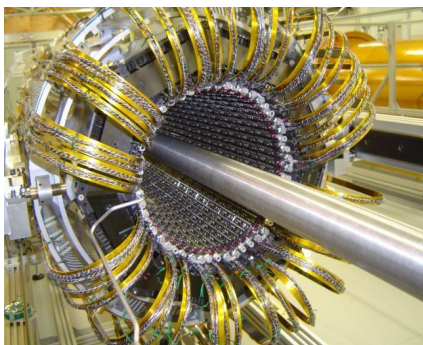
## CMS Tracker



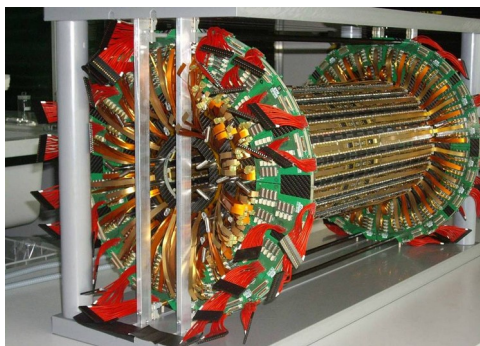


# Silicon Tracking Detectors

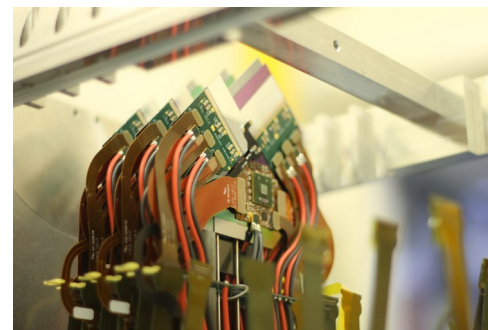
Silicon tracking detectors are used in almost all HEP experiments:  
Different sensor technologies, designs, operating conditions,....



**ATLAS Pixel Detector**



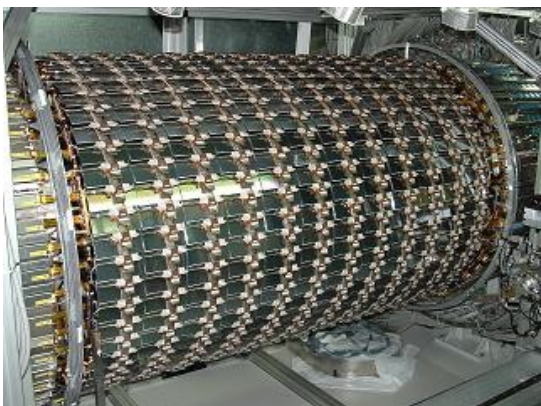
**CMS Pixel Detector**



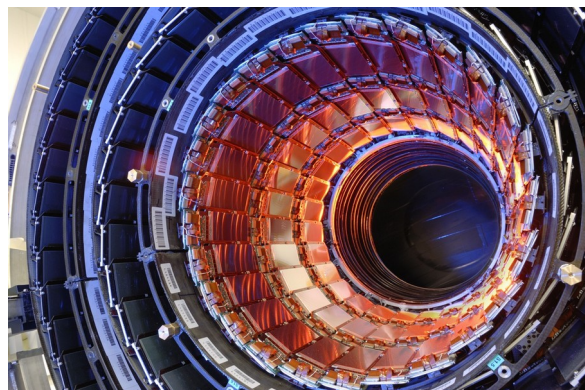
**LHCb VELO (New Velo for Run3:2022)**



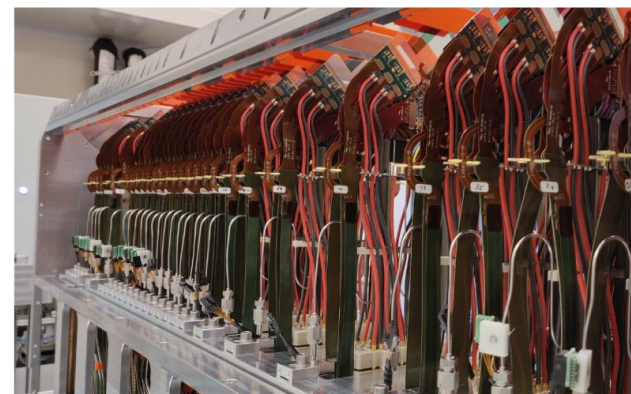
**ALICE ITS Barrel  
New ITS for Run3:2022)**



**ATLAS SCT Barrel**



**CMS Strip Tracker IB**



**LHCb VELO (New Velo for Run3:2022)**



**ALICE ITS Outer Barrel  
(Insertion Test 2021)**

# Silicon Sensors

## • Some characteristics of Silicon crystals

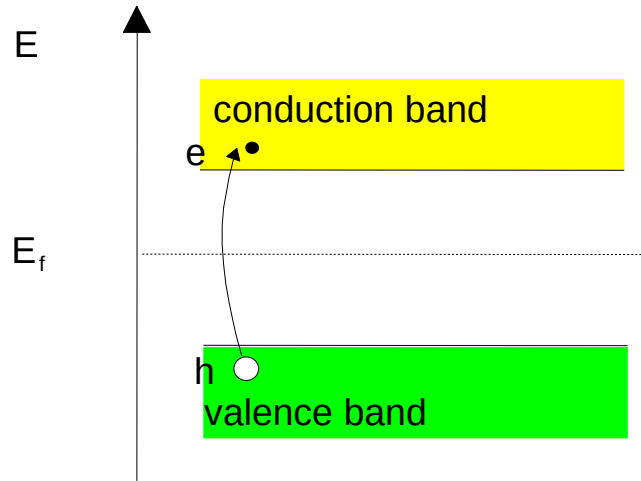
- **Small band gap**  $E_g = 1.12 \text{ eV}$   $E(\text{e-h pair}) = 3.6 \text{ eV}$  (  $30 \text{ eV}$  for gas detectors)
- **High specific density**  $2.33 \text{ g/cm}^3$  ;  $dE/dx$  (M.I.P.)  $3.8 \text{ MeV/cm}$   $106 \text{ e-h}/\mu\text{m}$  (average)
- **High carrier mobility**  $\mu_e = 1450 \text{ cm}^2/\text{Vs}$ ,  $\mu_h = 450 \text{ cm}^2/\text{Vs}$  fast charge collection ( $<10 \text{ ns}$ )
- **Very pure**  $< 1\text{ppm}$  impurities and  $< 0.1\text{ppb}$  electrical active impurities
- **Rigidity** of silicon allows thin self supporting structures
- **Detector production by microelectronic techniques**  
well known industrial technology, relatively low price, small structures easily possible

## • Alternative semiconductors

- **Diamond**
- Gallium arsenide (GaAs)
- Gallium nitride (GaN)
- **Silicon Carbide (SiC)**
- Germanium (Ge)

	Diamond	SiC (4H)	GaAs	Si	Ge
Atomic number Z	6	14/6	31/33	14	32
Bandgap $E_g$ [eV]	5.5	3.3	1.42	1.12	0.66
$E(\text{e-h pair})$ [eV]	13	7.6-8.4	4.3	3.6	2.9
density [ $\text{g/cm}^3$ ]	3.52	3.22	5.32	2.33	5.32
e-mobility $\mu_e$ [ $\text{cm}^2/\text{Vs}$ ]	1800	800	8500	1450	3900
h-mobility $\mu_h$ [ $\text{cm}^2/\text{Vs}$ ]	1200	115	400	450	1900

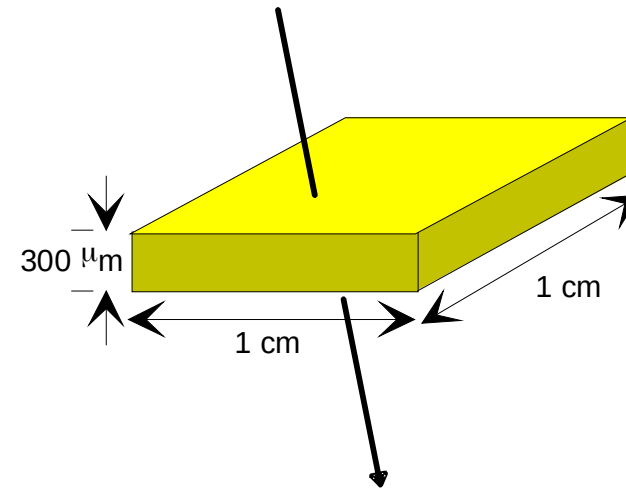
# How to obtain the signal?



In a pure intrinsic (undoped) semiconductor the electron density  $n$  and hole density  $p$  are equal.

$$n = p = n_i \quad \text{For Silicon: } n_i = 1.45 \cdot 10^{10} \text{ cm}^{-3}$$

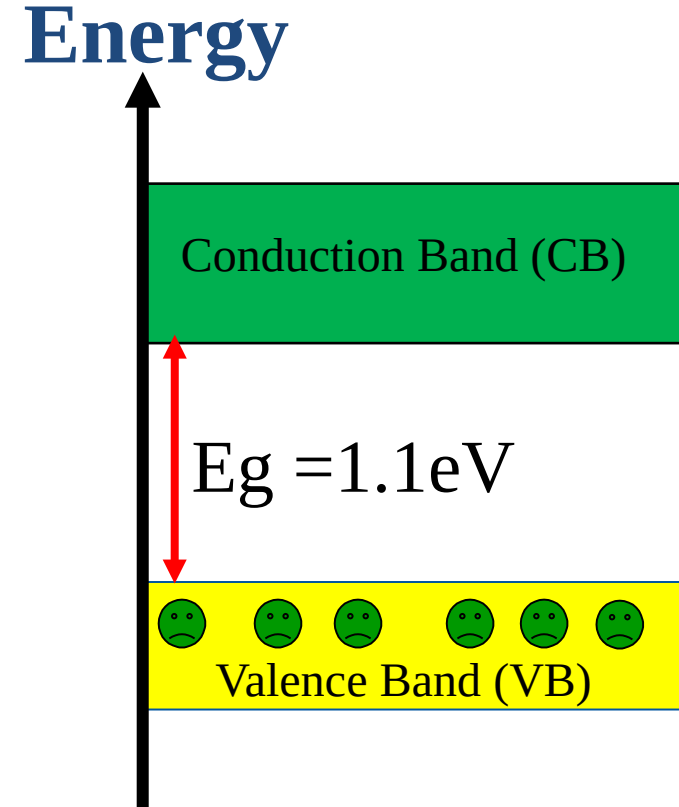
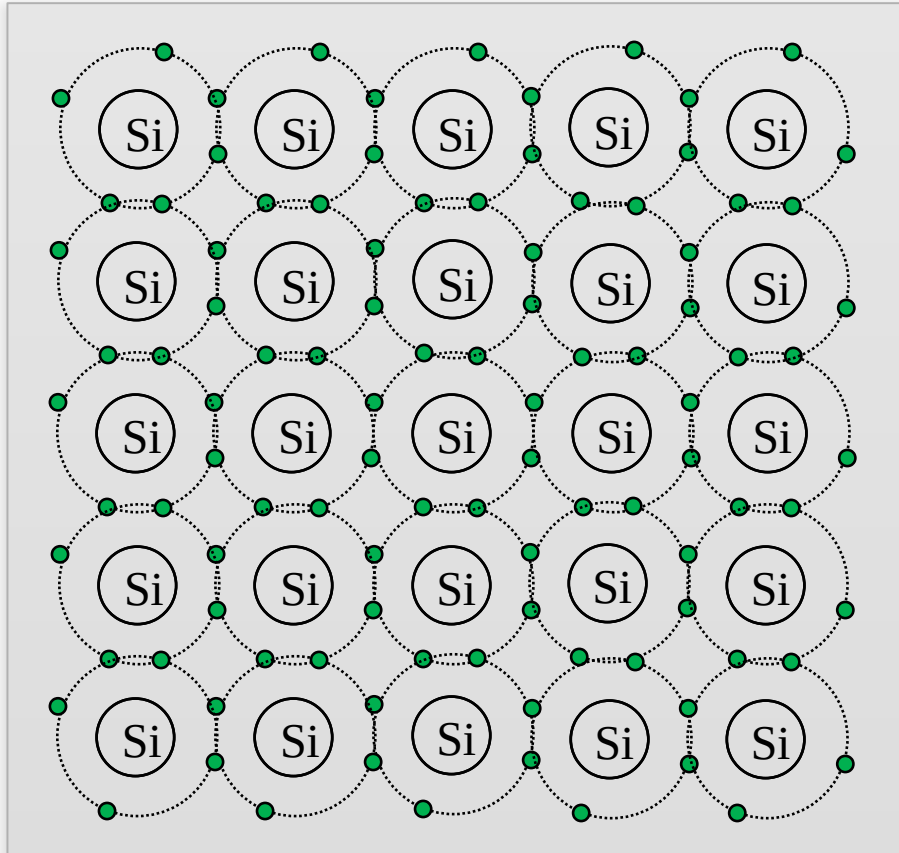
$4.5 \cdot 10^8$  free charge carriers in this volume,  
but only  $\sim 32000$  e-h pairs produced by a M.I.P.



Reduce number of free charge carriers, i.e. **deplete** the detector

**Most detectors make use of reverse biased p-n junctions**

# Covalent Bonding of Pure Silicon

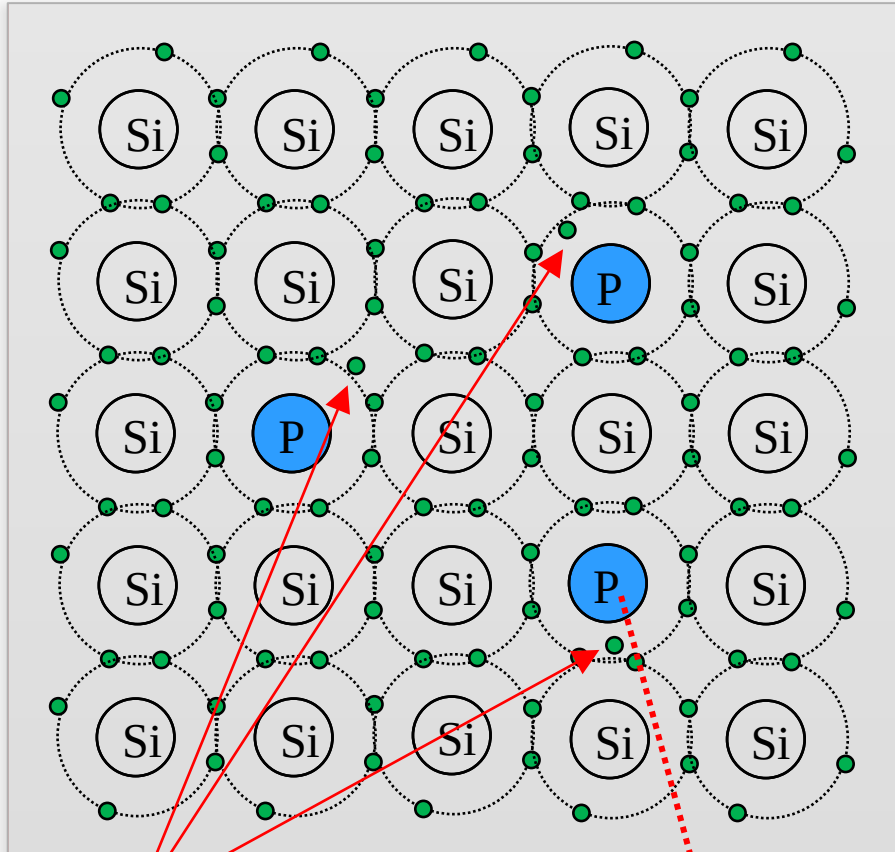


Silicon atoms share valence electrons to form insulator-like bonds.

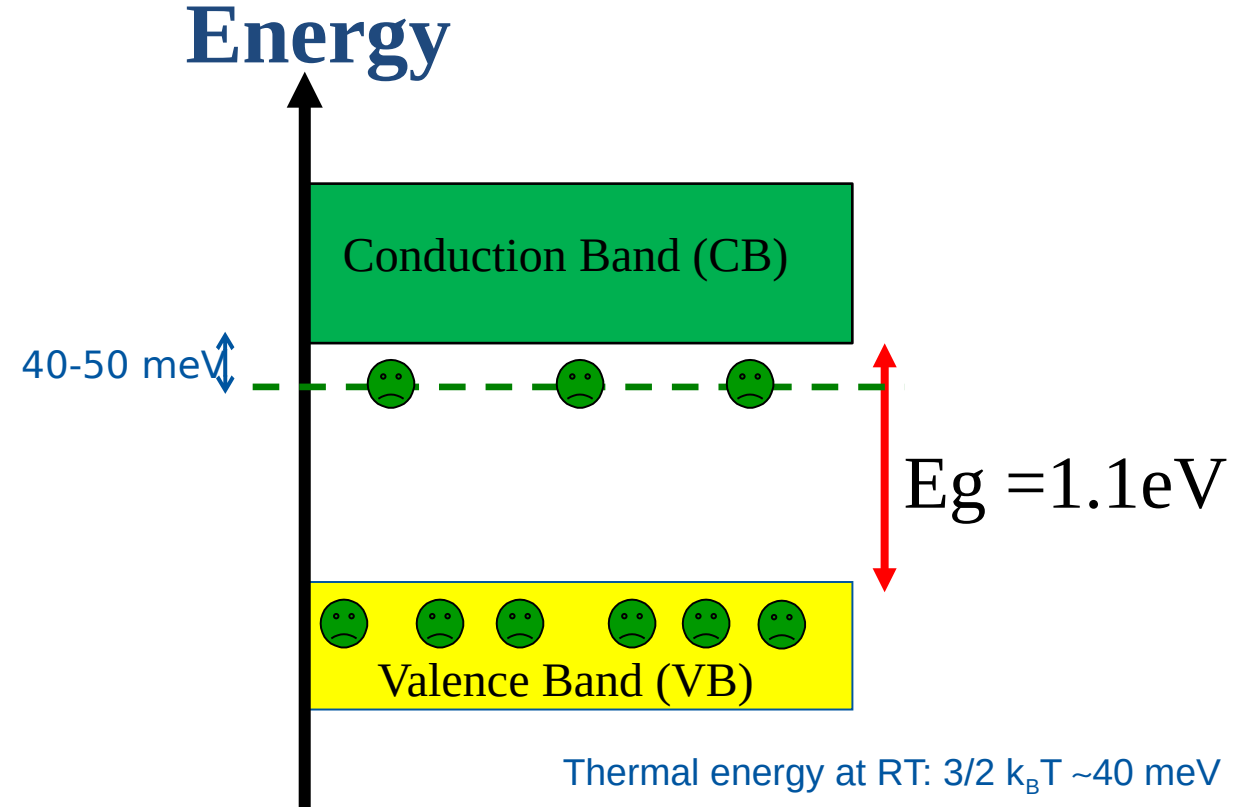
Thermal energy at RT:  $3/2 k_B T \sim 40\text{ meV}$

# Electrons in n-type silicon with phosphorus dopant

Donor atoms provide excess electrons  
to form n-type silicon



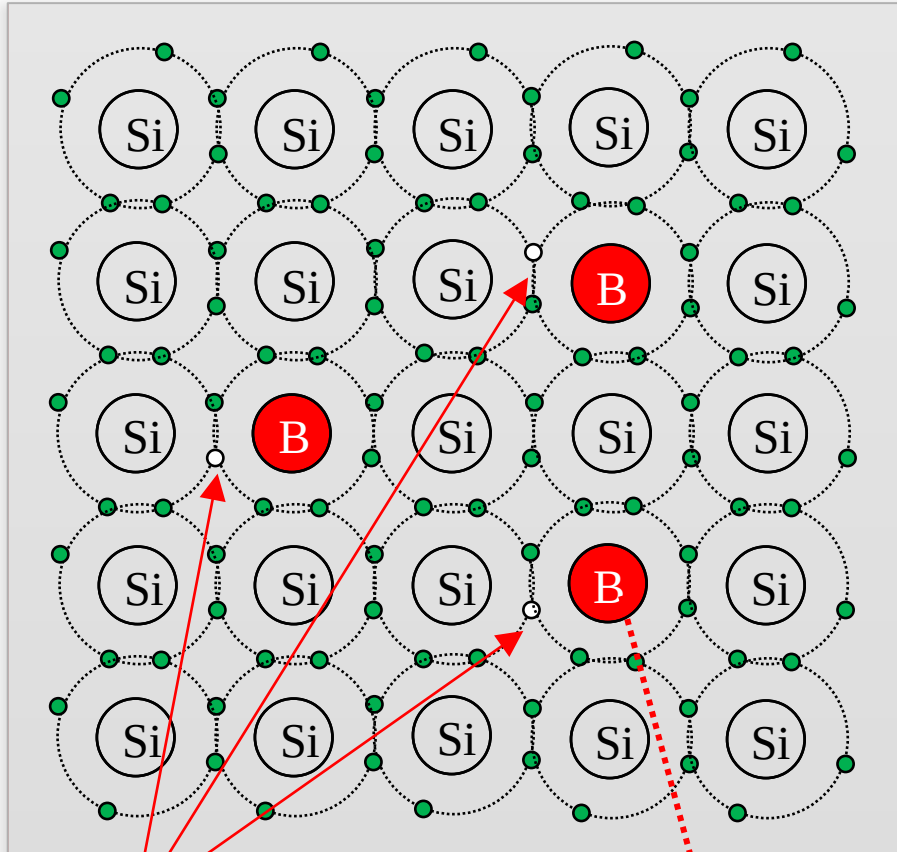
Excess electron (-) Phosphorus atom serves  
as n-type dopant



electrons are the majority  
carriers in n-type silicon

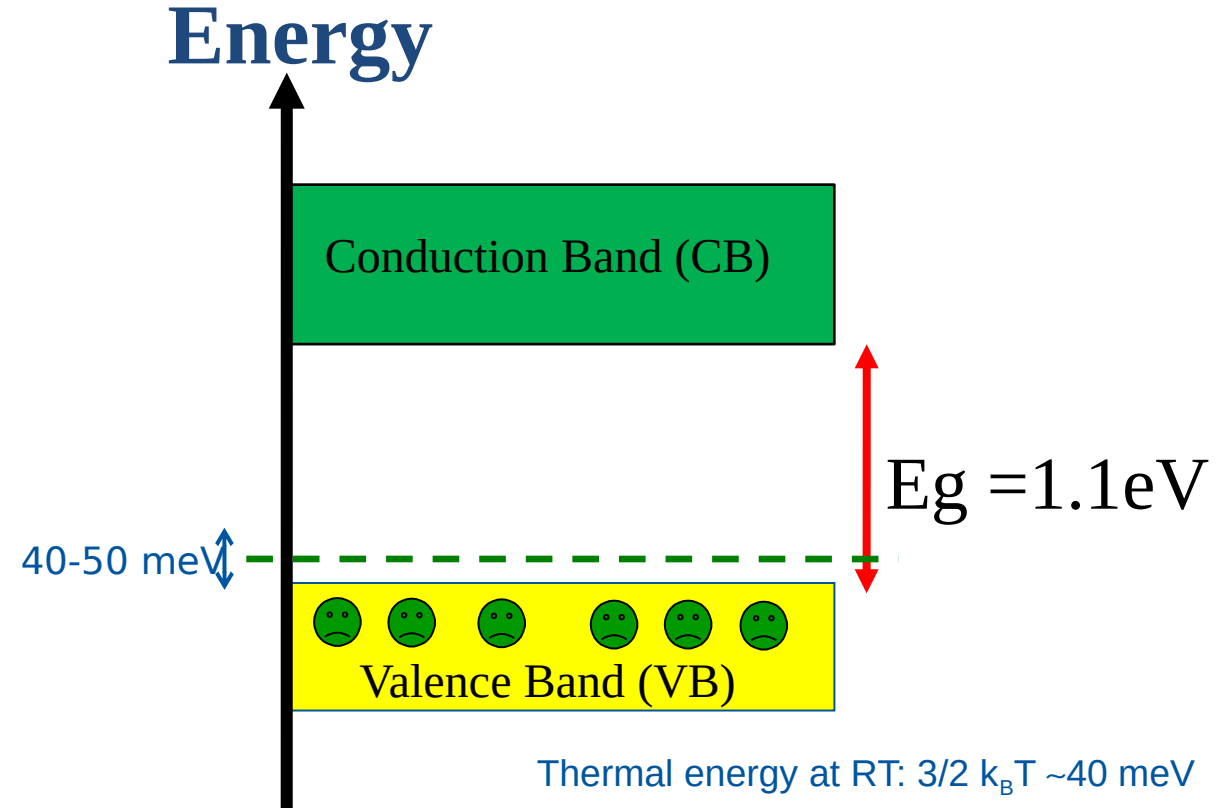
# Holes in p-type silicon with boron dopant

Acceptor atoms provide holes  
to form p-type silicon



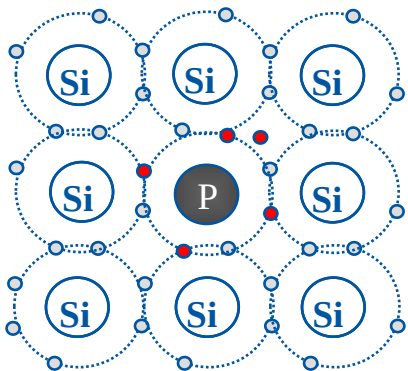
holes(+)

boron atom serves as  
p-type dopant



holes are the majority  
carriers in p-type silicon

e.g. Phosphorus



- **resistivity  $\rho$**

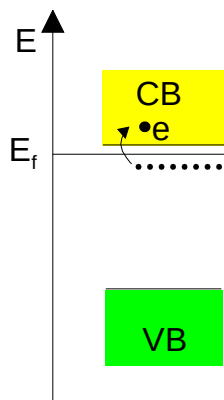
- carrier concentration  $n, p$
- carrier mobility  $\mu_n, \mu_p$

$$\rho = \frac{1}{q_0} (\mu_n n + \mu_p p)$$

	detector grade	electronics grade
doping	$10^{12} \text{ cm}^{-3}$	$10^{17} \text{ cm}^{-3}$
resistivity	5 k · cm	1 · cm

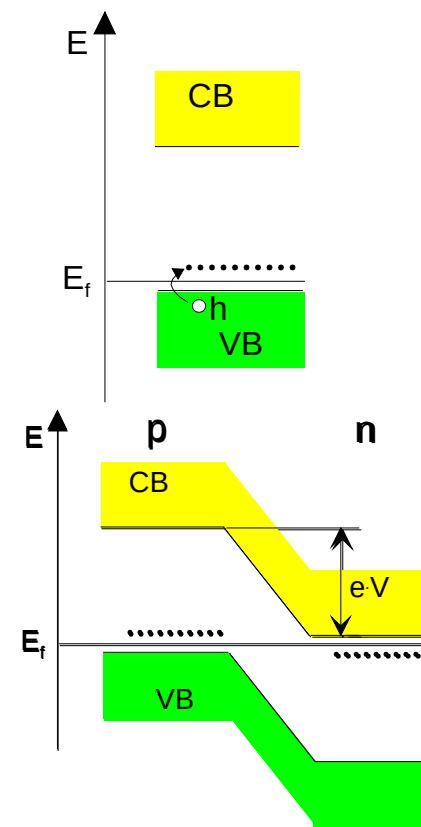
- **Doping: n-type silicon**

- add elements from V<sup>th</sup> group **donors** (P, As,...)
- electrons are majority carriers



- **Doping: p-type silicon**

- add elements from III<sup>rd</sup> group **acceptors** (B,...)
- holes are majority carriers



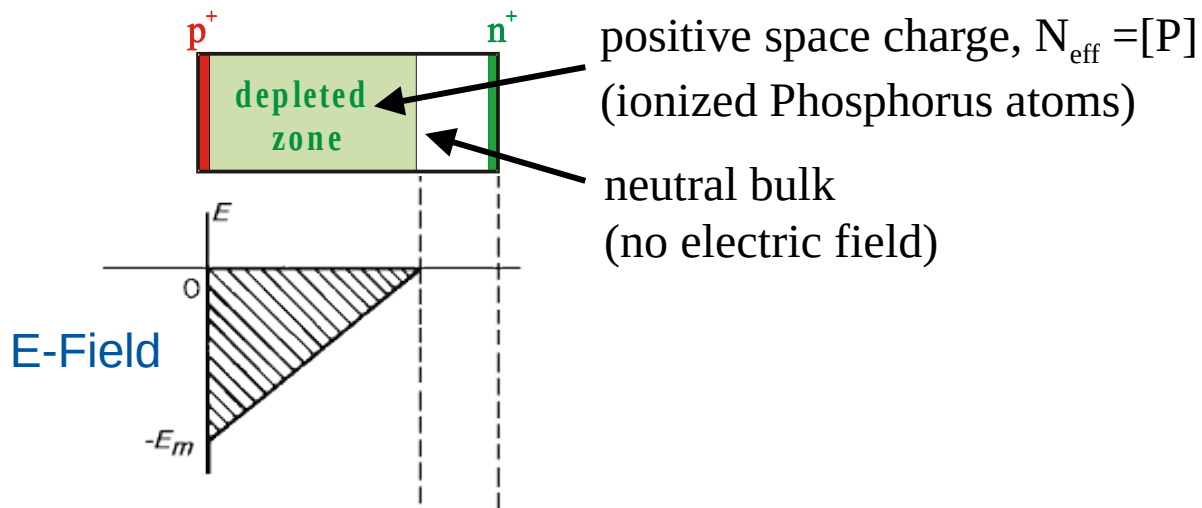
## p-n junction

There must be a single Fermi level!

- band structure deformation
- potential difference
- depleted zone



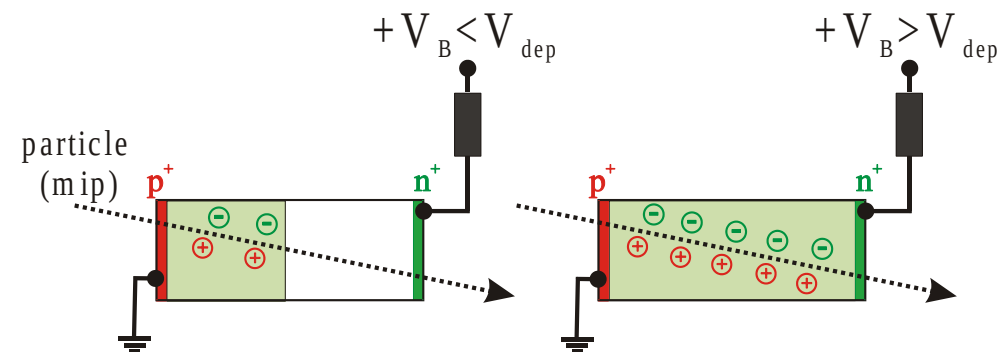
- Below depletion



- Depletion Voltage  $V_{\text{dep}}$

- sensor depleted of free charge carriers
- electric field throughout complete device
- complete sensor volume sensitive (active)
- Example:
  - $d = 300 \mu\text{m}$  and  $N_{\text{eff}} = [P] = 1.5 \cdot 10^{12} \text{ cm}^{-3}$  ( $\rho = 3 \text{ k}\Omega\text{cm}$ )
  - Depletion Voltage:  $V_{\text{dep}} = 100\text{V}$

- Depleted zone growth with increasing voltage ( $w \propto \sqrt{V_B}$ )



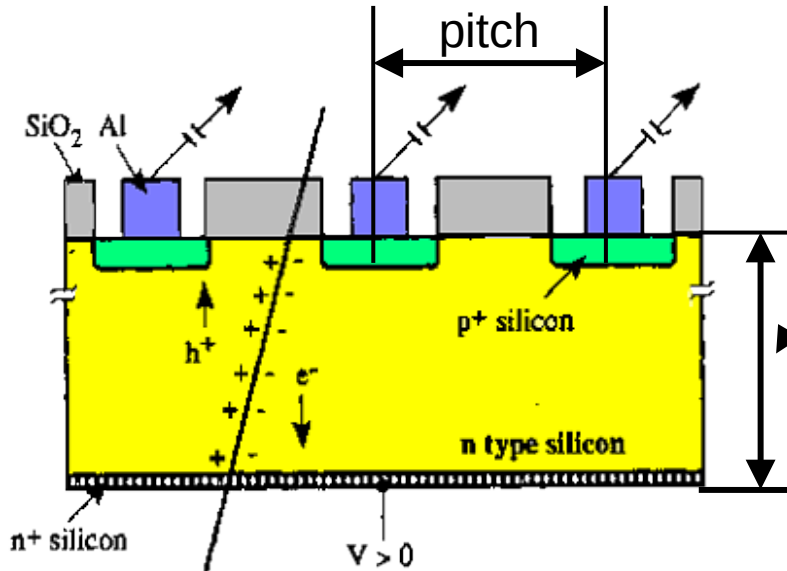
- Full charge collection only for fully depleted detector ( $V_B > V_{\text{dep}}$ )

depletion voltage  $V_{\text{dep}}$       detector thickness  $d$

$$V_{\text{dep}} = \frac{q_0}{\epsilon \epsilon_0} \cdot |N_{\text{eff}}| \cdot d^2$$

effective space charge density  $N_{\text{eff}}$

- Segmentation of the p<sup>+</sup> layer into strips (Diode Strip Detector) and connection of strips to individual read-out channels gives spatial information



Typical thickness: 300μm (150μm-500μm used)

- using n-type silicon with a resistivity of = 2 KΩcm ( $N_D \sim 2.2 \cdot 10^{12} \text{cm}^{-3}$ ) results in a depletion voltage  $\sim 150 \text{ V}$

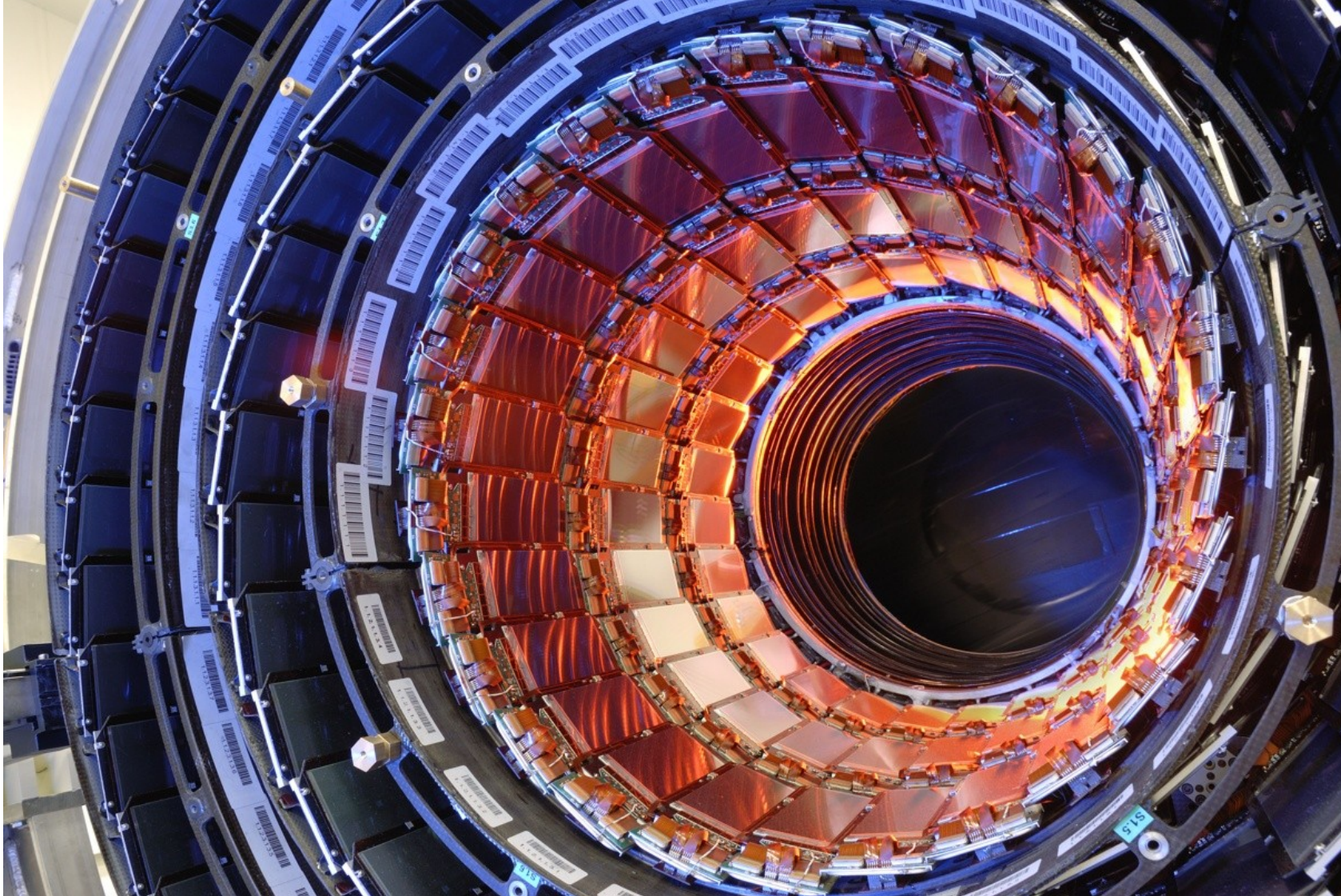
- Resolution depends on the pitch  $p$  (distance from strip to strip)

- e.g. detection of charge in binary way (threshold discrimination) and using center of strip as measured coordinate results in

$$\sigma = \frac{p}{\sqrt{12}}$$

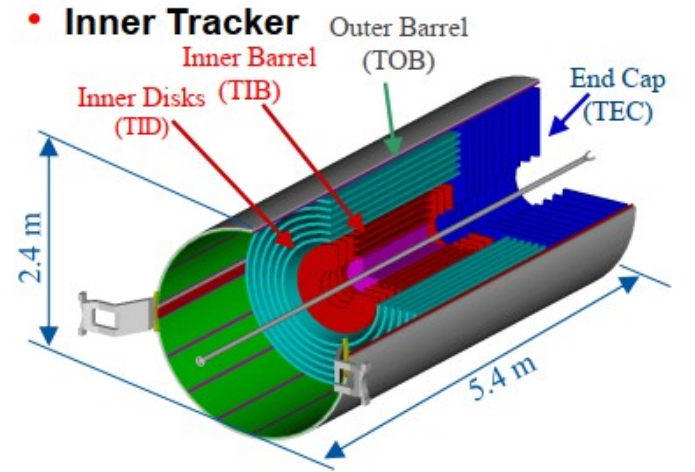
typical pitch values are 20 μm– 150 μm 50 μm pitch results in 14.4 μm resolution

# Present LHC Tracking Sensors



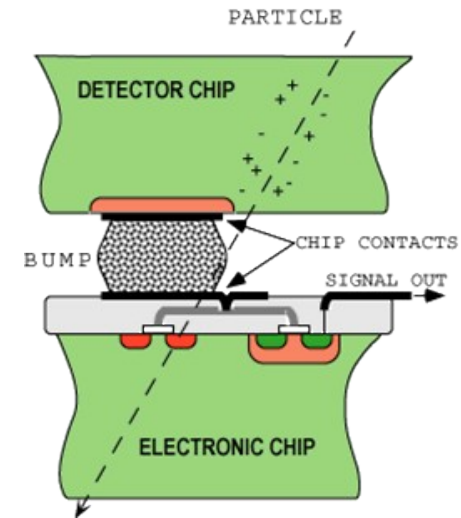
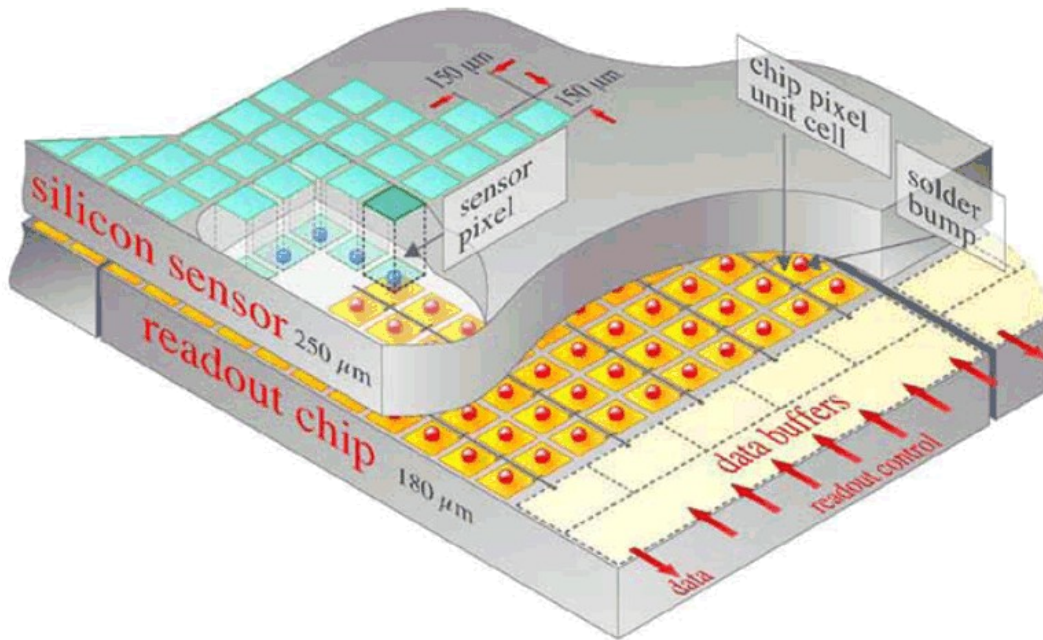
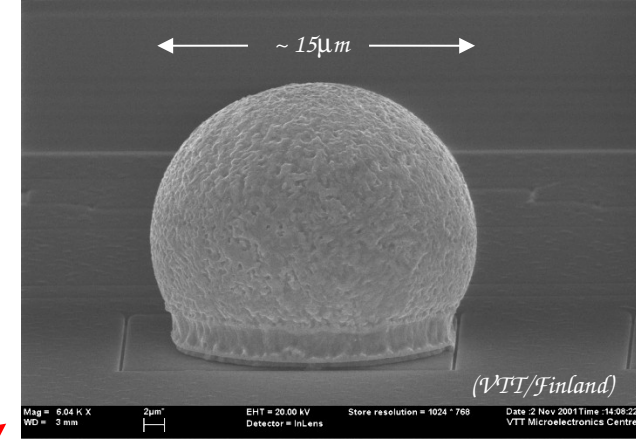
CMS Tracker

... 11.4 million strips



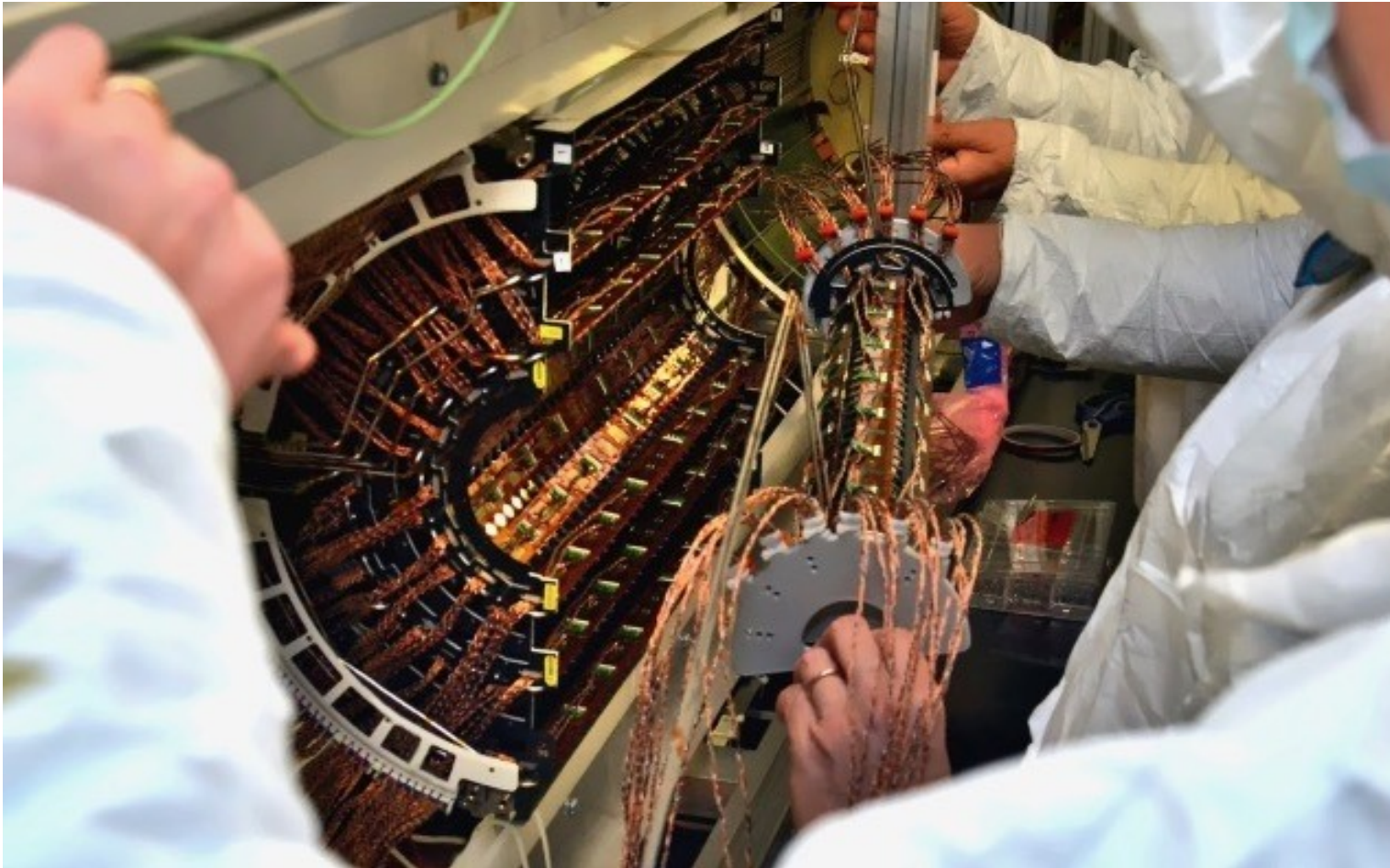
- HAPS – Hybrid Active Pixel Sensors
  - segment silicon to diode matrix with high granularity ( true 2D, no reconstruction ambiguity)
  - readout electronic with same geometry (every cell connected to its own processing electronics)
  - connection by “bump bonding”
  - requires sophisticated readout architecture
  - Hybrid pixel detectors are used in LHC experiments: ATLAS, ALICE (from Run3 monolithic), CMS and LHCb

## Solder Bump: Pb-Sn

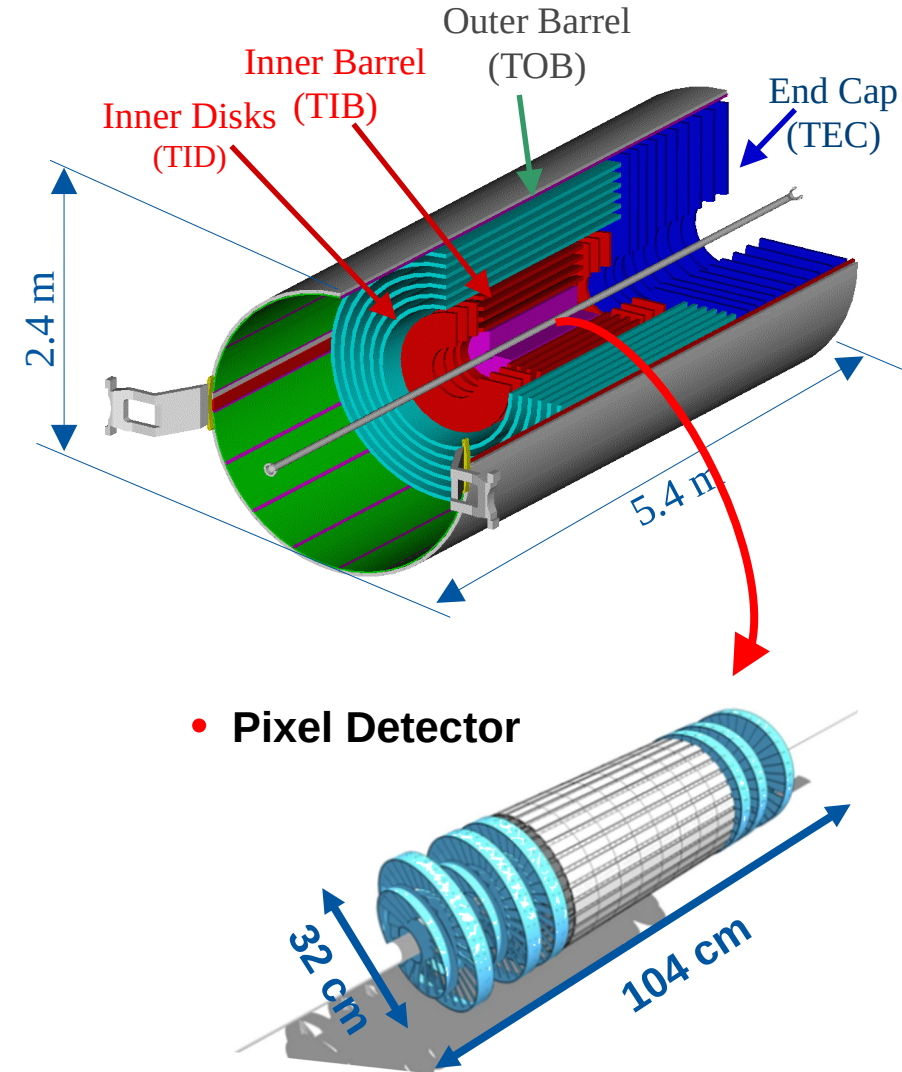


## Flip-chip technique

# Present LHC Tracking Sensors



CMS Pixel (Installation after maintenance in 2021)



- Collected charge for a Minimum Ionizing Particle (MIP)

- **Mean energy loss**

$dE/dx$  (Si) = 3.88 MeV/cm

116 keV for 300 $\mu$ m thickness

- **Most probable energy loss**

$\approx$  0.7 mean

81 keV

- **3.6 eV to create an e-h pair**

108 e-h /  $\mu$ m (mean)

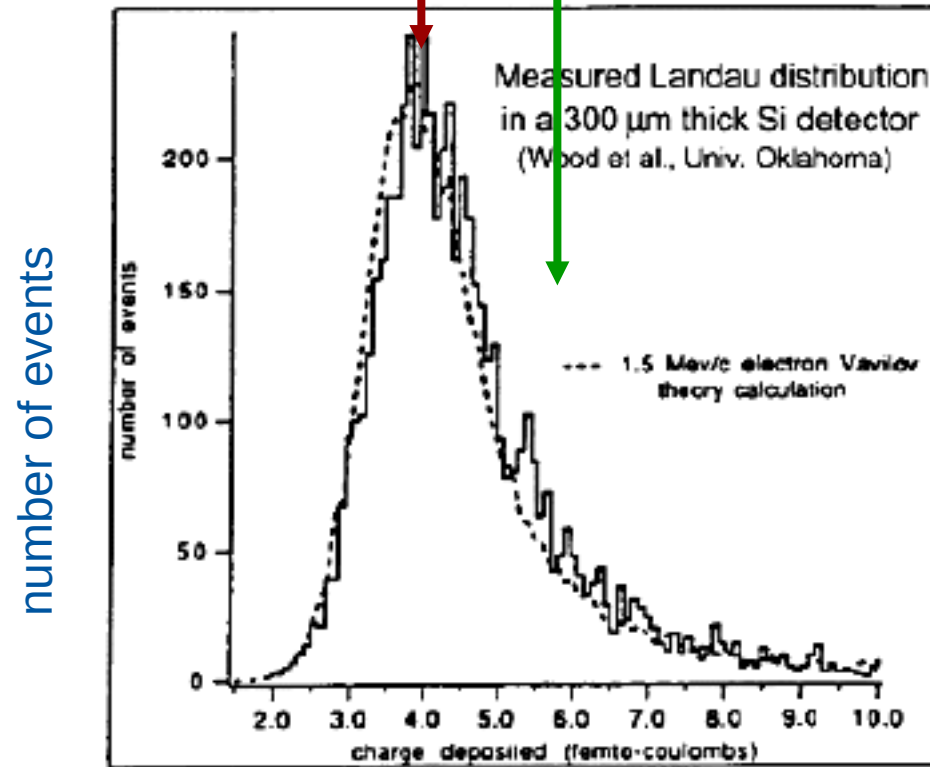
72 e-h /  $\mu$ m (most probable)

- **Most probable charge (300  $\mu$ m)**

$\approx$  22500 e       $\approx$  3.6 fC

**Most probable charge  $\approx$  0.7 mean**

**Mean charge**

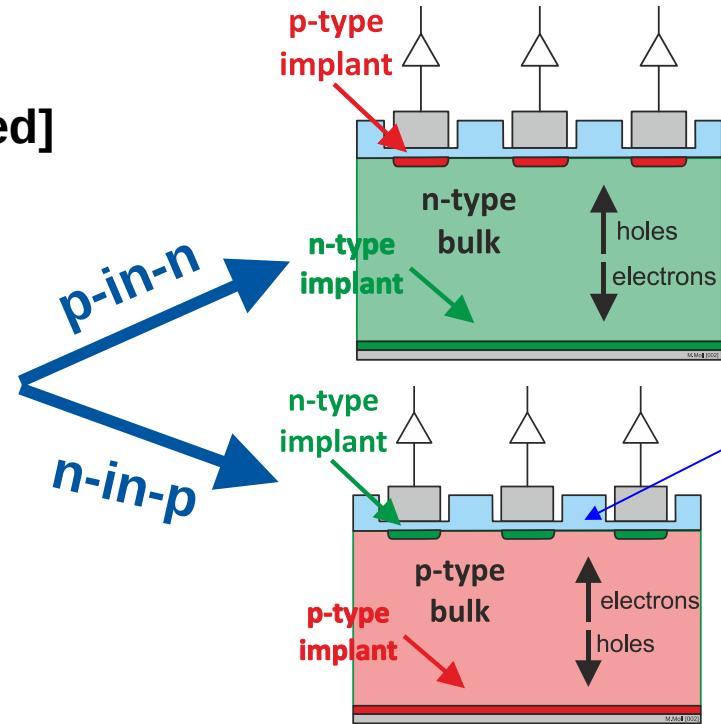
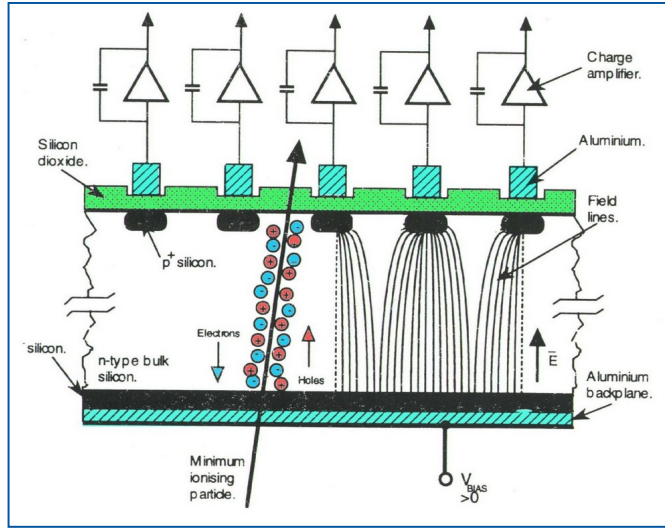
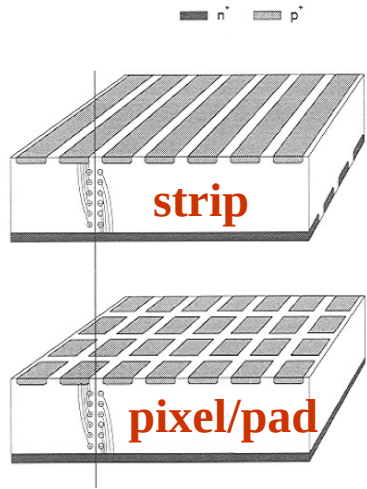


number of events

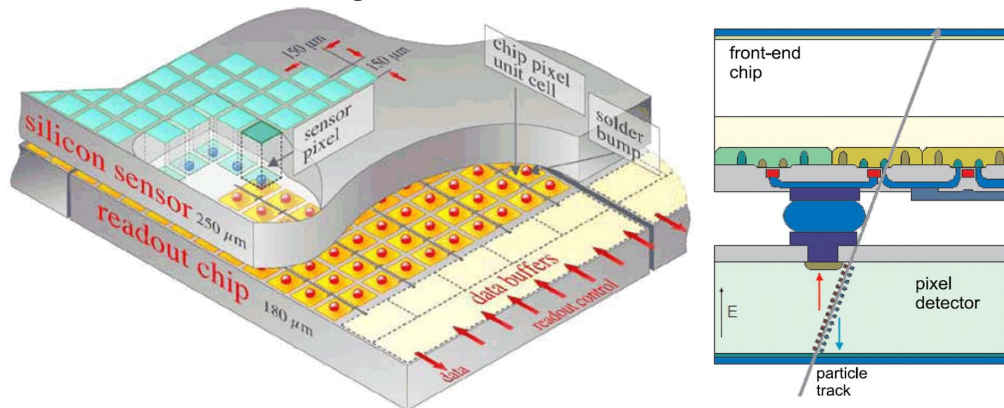
charge deposited [fC]

## Main sensor concepts:

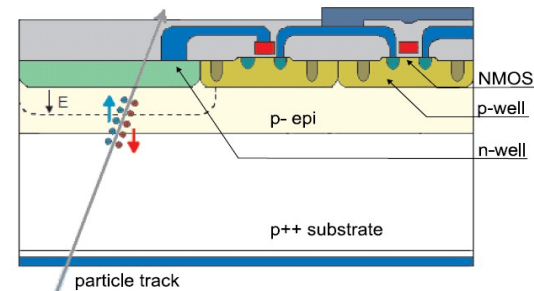
### (Mini) Strip Detector [AC coupled]



### Hybrid Pixel Detector



### Monolithic CMOS Pixel Detector



# Radiation Damage

- Damage to dielectric layers and interfaces (not covered)
- Damage to the semiconductor bulk (introduction)



## Silicon detectors upgrades and operation

### - Radiation Hardness -

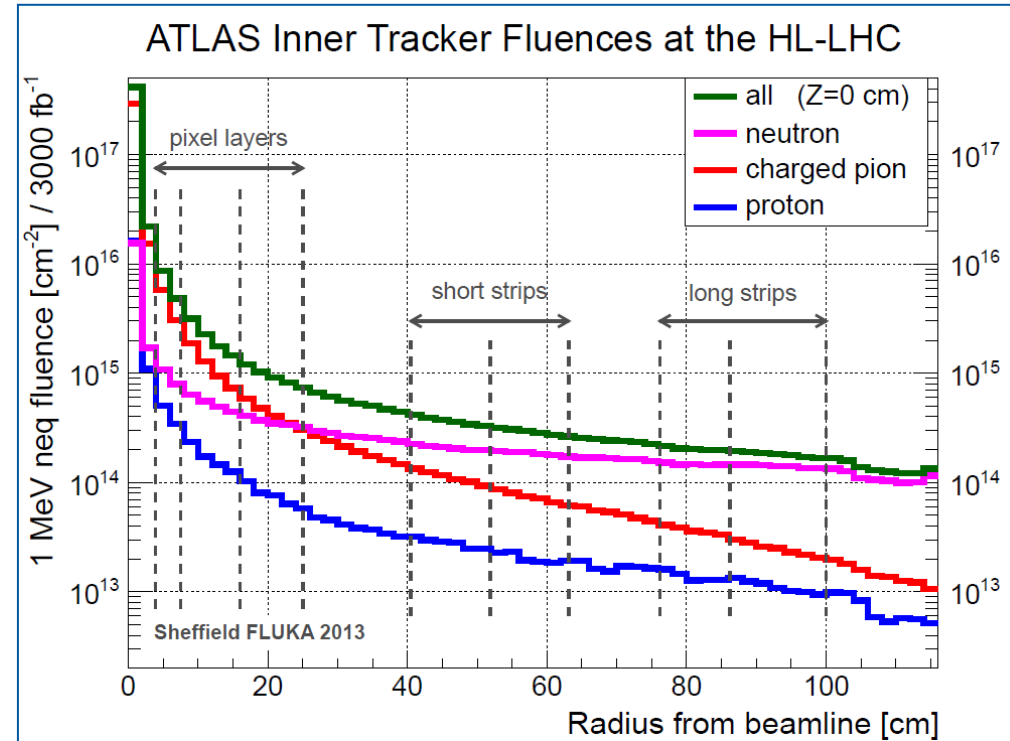
- **LHC operation**
- **HL-LHC (High Luminosity LHC)**
  - detector developments for HL-LHC
    - starting after LS3 (~2025-27);
    - expect 4000 fb<sup>-1</sup> (nominal LHC was 300 fb<sup>-1</sup>)
- **HL-LHC operation & upgrades**
  - operation of HL-LHC
    - damage modelling, evaluation, mitigation
  - ATLAS Pixel replacement, LHCb upgrade, ...
- **FCC – Future Circular Collider**
  - ..also FCC-ee

### • Increasing radiation levels

- Semiconductor detectors will face  $>10^{16}$  n<sub>eq</sub>/cm<sup>2</sup> (**HL-LHC**) and  $>7 \times 10^{17}$  n<sub>eq</sub>/cm<sup>2</sup> (**FCC-hh**)
  - detectors used at LHC cannot be operated after such irradiation

### • New requirement and new detector technologies

- New requirements or opportunities lead to new technologies (e.g. HV-CMOS, LGAD,...) which need to be evaluated and optimized in terms of **radiation hardness and/or 4D tracking capabilities**



[I. Dawson, P. S. Miyagawa, Sheffield University, Atlas]

## Main effects:

- **Ionizing Energy Loss (IEL)**

- Surface effect: trapping charges in the oxide
- Main effect for electronics (with SEUs)

- **Non Ionizing Energy Loss (NIEL)**

- Bulk effect: Si atoms displaced from lattice position
- Interstitials and Vacancies formed (Frenkel pairs) resulting in point and cluster defects
- Creation of defect states in the band gap:

- **I. Change of internal E-Field**

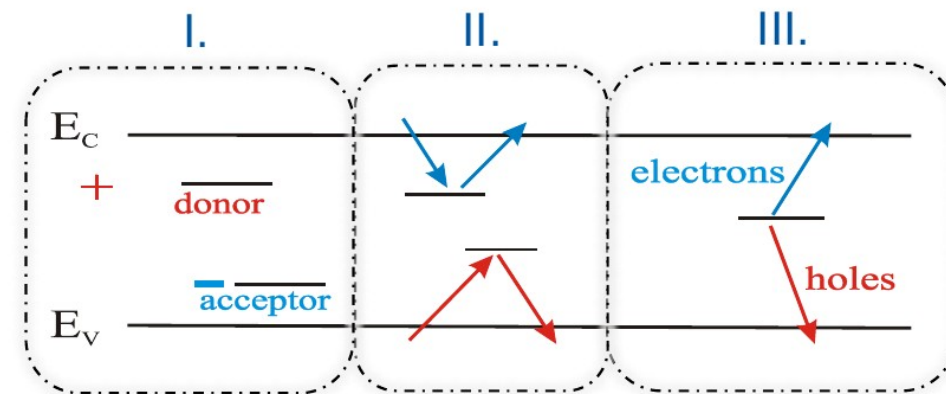
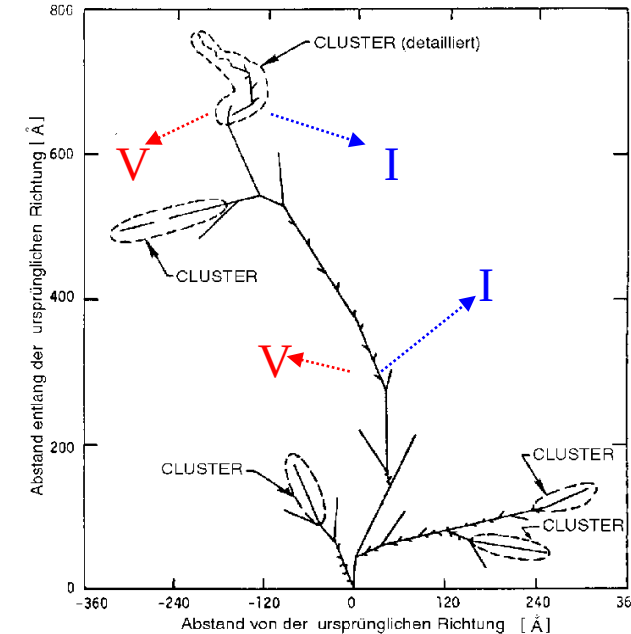
charged defects change depletion,  
leading to under depletion, loss of signal

- **II. Charge trapping**

loss of signal charge

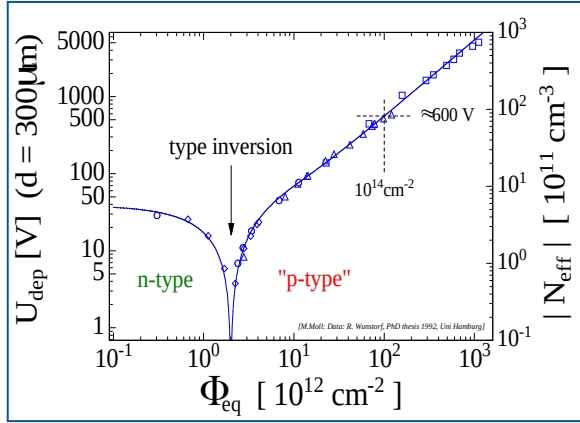
- **III. Increase of leakage**

increase of power consumption  
increase of noise

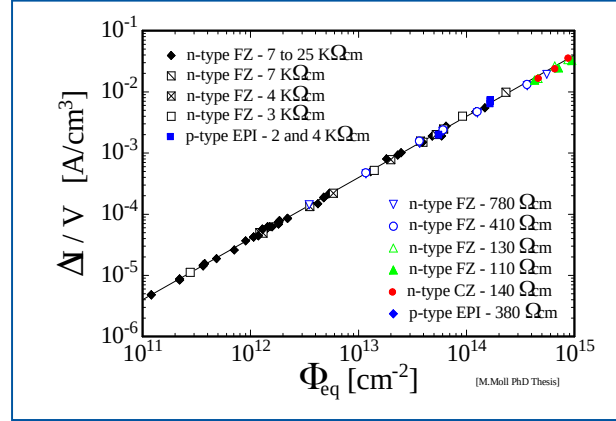


# Radiation Damage Summary

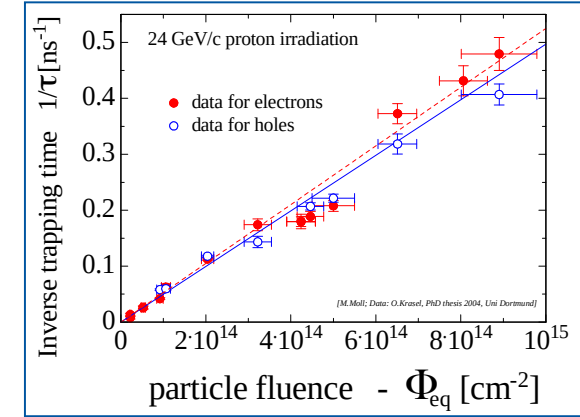
- Macroscopic bulk effects:



Depletion Voltage ( $N_{eff}$ )

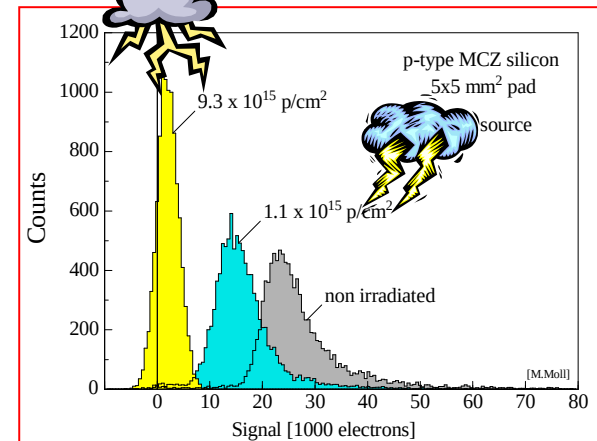
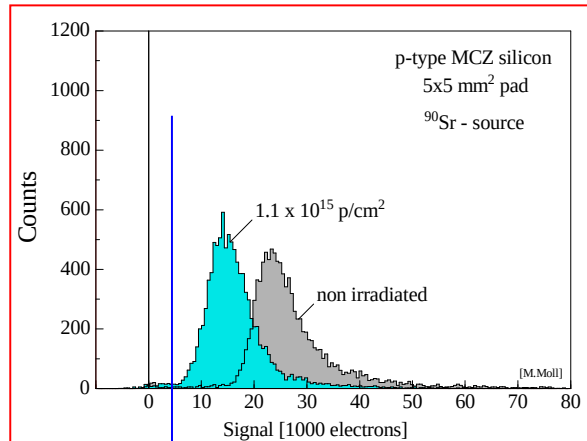
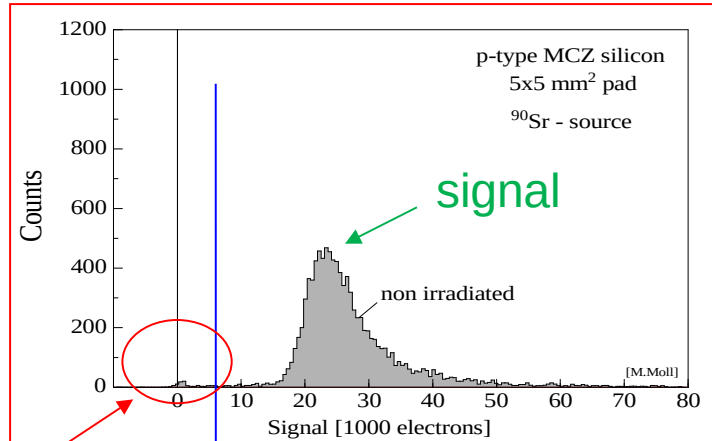


Leakage Current



Charge Trapping

- Signal to Noise ratio is quantity to watch (material + geometry + electronics)



noise

Cut (threshold)

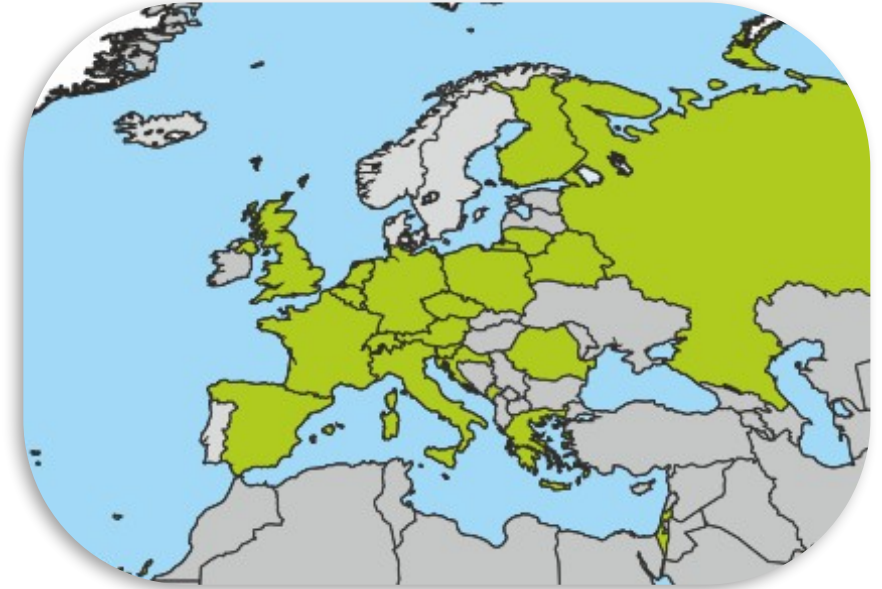
# Radiation Hard Detectors

How to increase radiation hardness?

- RD50: 66 institutes and 420 members

## 51 European institutes

**Austria** (HEPHY), **Belarus** (Minsk), **Czech Republic** (Prague (3x)), **Finland** (Helsinki, Lappeenranta ), **France** (Marseille, Paris, Orsay), **Germany** (Bonn, Dortmund, Freiburg, Göttingen, Hamburg (Uni & DESY), Karlsruhe, Munich (MPI & MPG HLL)), **Greece** (Demokritos), **Italy** (Bari, Perugia, Pisa, Trento, Torino), **Croatia** (Zagreb), **Lithuania** (Vilnius), **Montenegro** (Montenegro), **Netherlands** (NIKHEF), **Poland** (Krakow), **Romania** (Bucharest), **Russia** (Moscow, St.Petersburg), **Slovenia** (Ljubljana), **Spain** (Barcelona(3x), Santander, Sevilla (2x), Valencia), **Switzerland** (CERN, PSI, Zurich), **United Kingdom** (Birmingham, Glasgow, Lancaster, Liverpool, Oxford, Manchester, RAL)



## 8 North-American institutes

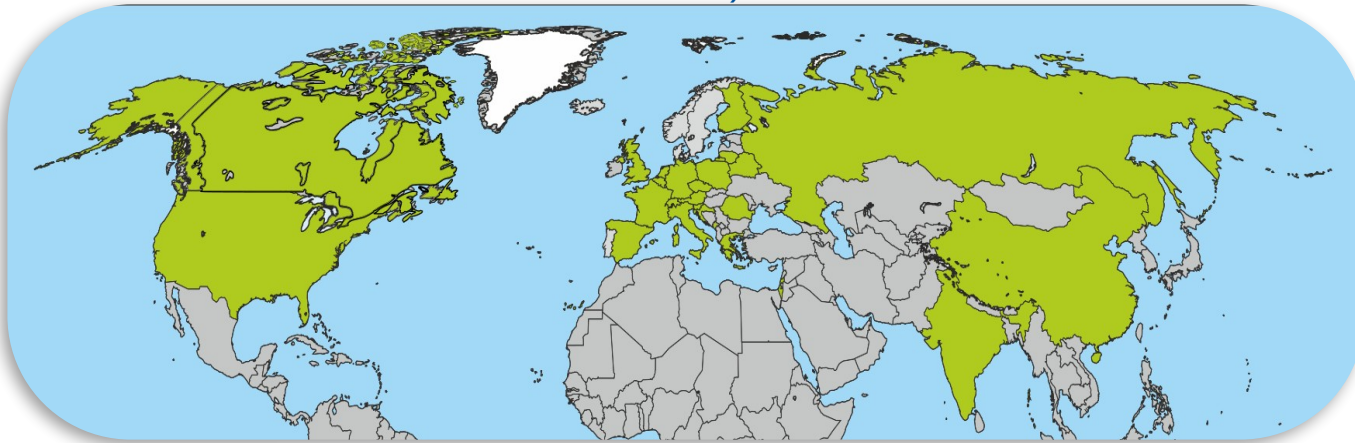
**Canada** (Ottawa), **USA** (BNL, Brown Uni, Fermilab, LBNL, New Mexico, Santa Cruz, Syracuse)

## 1 Middle East institute

**Israel** (Tel Aviv)

## 6 Asian institutes

**China** (Beijing-IHEP, Dalian, Hefei, Jilin, Shanghai),  
**India** (Delhi)



Full member list: [www.cern.ch/rd50](http://www.cern.ch/rd50)

## Scientific strategies:

- I. Material engineering
- II. Device engineering
- III. Change of detector operational conditions

CERN-RD39 (closed, now part of RD50)  
“Cryogenic Tracking Detectors”  
operation at 100-200K to reduce charge loss

### • Defect Engineering of Silicon

*Deliberate incorporation of impurities or defects into the silicon bulk to improve radiation tolerance of detectors*

- **Needs:** Profound understanding of radiation damage
  - microscopic defects, macroscopic parameters
  - dependence on particle type and energy
  - defect formation kinetics and annealing
- **Examples:**
  - Oxygen rich Silicon (DOFZ, Cz, MCZ, EPI)
  - Oxygen dimer & hydrogen enriched Si
  - Pre-irradiated Si
  - Influence of processing technology

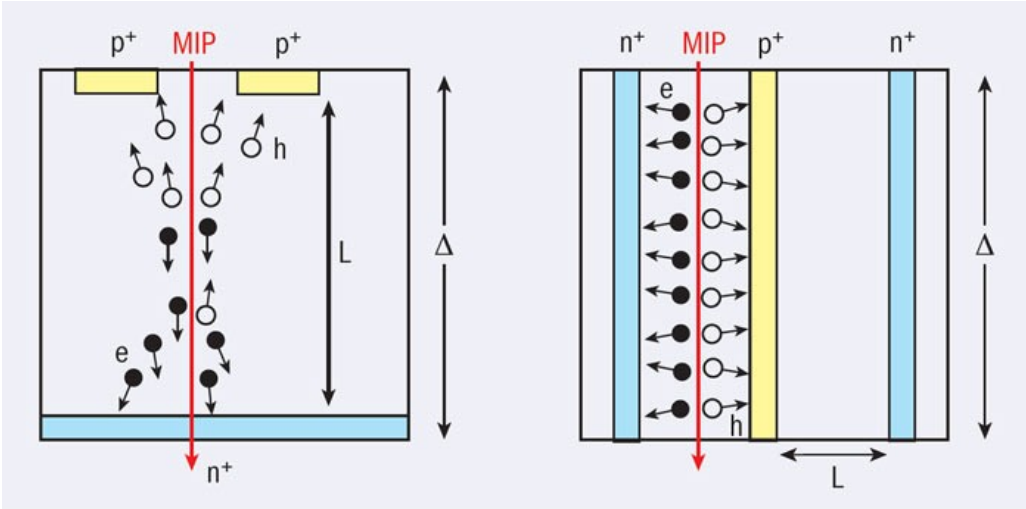
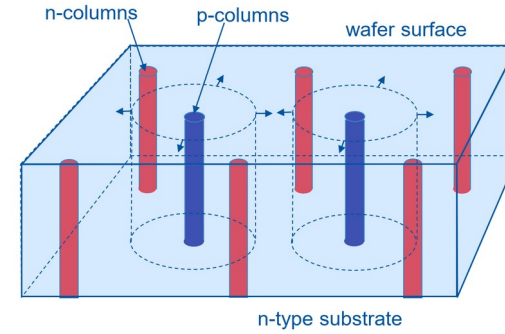
### • New Materials

- Silicon Carbide (SiC), Gallium Nitride (GaN)
- Diamond (CERN RD42 Collaboration)
- Amorphous silicon, Gallium Arsenide

### • Device Engineering (New Detector Designs)

- p-type silicon detectors (n-in-p)
- thin detectors, epitaxial detectors
- 3D detectors and LGAD - Low Gain Avalanche Detector
- Cost effective detectors
- Monolithic devices – HV-CMOS

# Device engineering example: 3D Hybrid Pixel Detectors

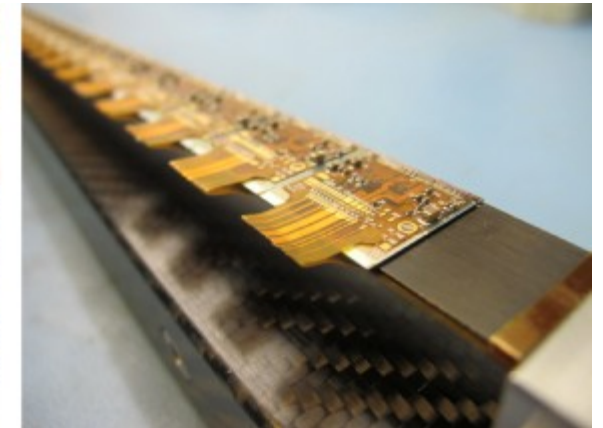


Array of narrow electrode columns ( $\sim 5\text{-}10\mu\text{m}$ ) passing through the silicon thickness (micromachining):

- Depletion voltage prop. spacing<sup>2</sup>
- Collection time prop. spacing
- Reduced charge sharing
- More suited to high radiation environment

Connected to standard pixel ASIC – hybrid pixel detector

Installed 2014 in ATLAS IBL  
(Inner b-layer)  
&  
Inner pixel layers  
for LHC phase II (2028)



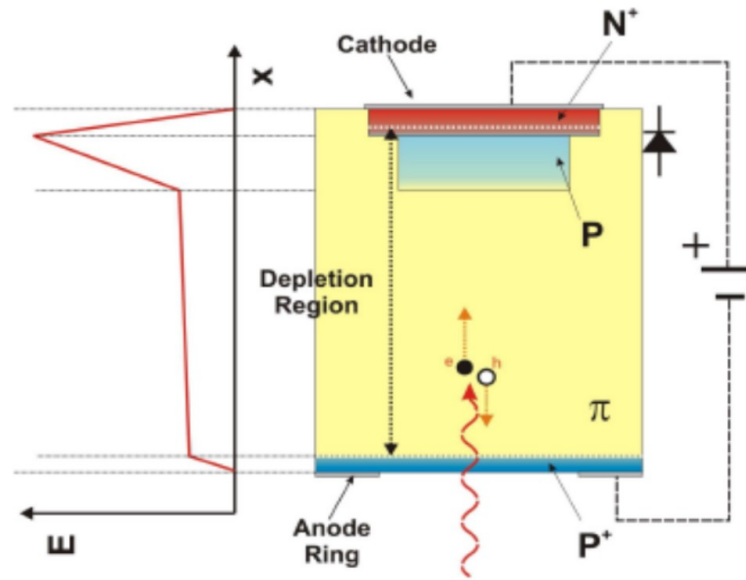
# Device engineering example 2: Low Gain Avalanche Detectors (LGAD)

**Highly doped p-implant leads to charge multiplication through impact ionization**

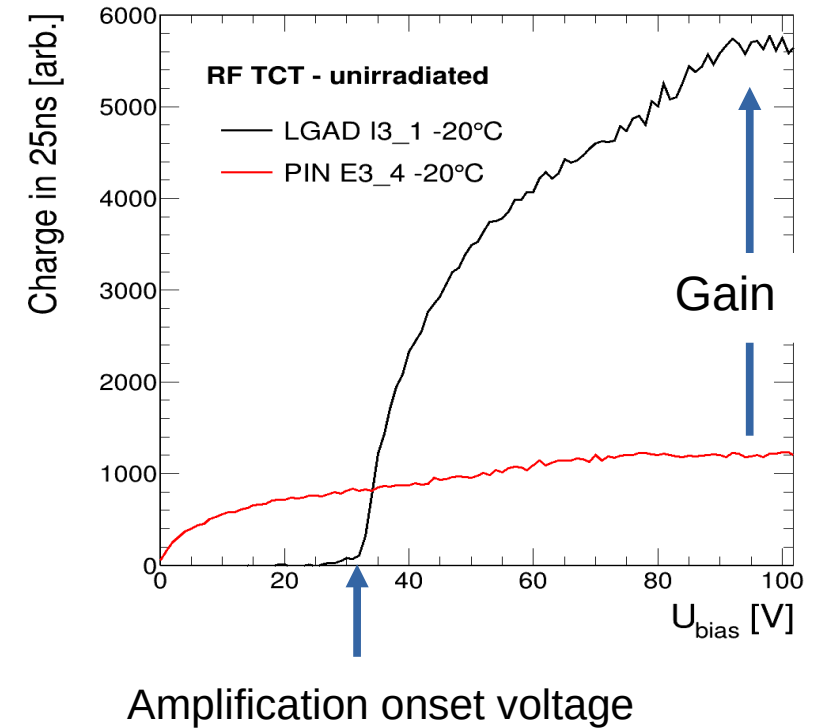
-- Larger signal and faster rise time.

**LGADs are based on the APD concept but have a lower gain, optimized for 4D-tracking applications:**

- .. fast signal rise time
- .. optimal S/N ratio
- .. reduced cross-talk



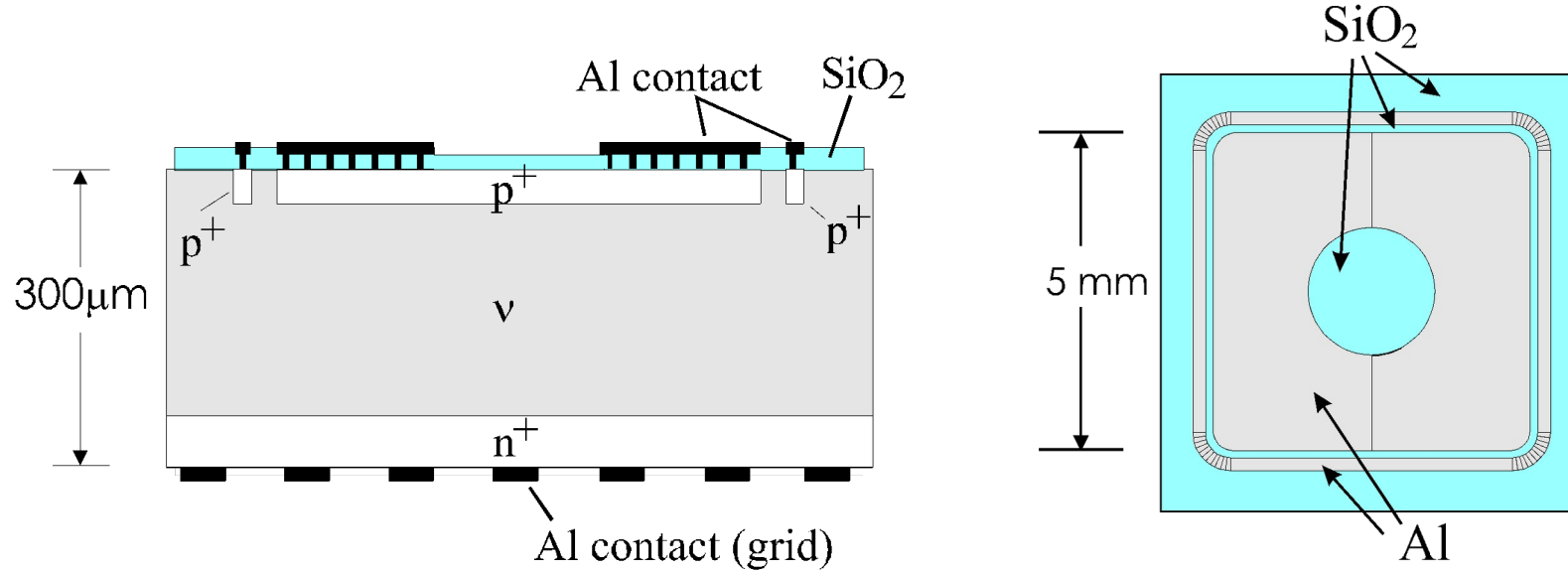
M. Carulla,  
*Low Gain Avalanche Detectors*





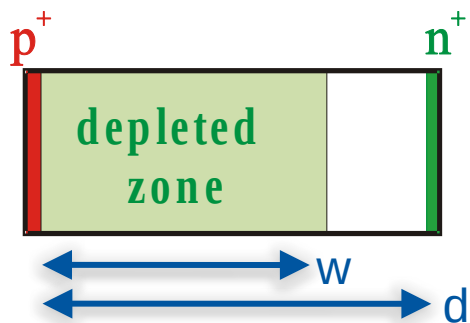
# Characterization Techniques

What are we going to measure  
in our “hands-on” workshop?



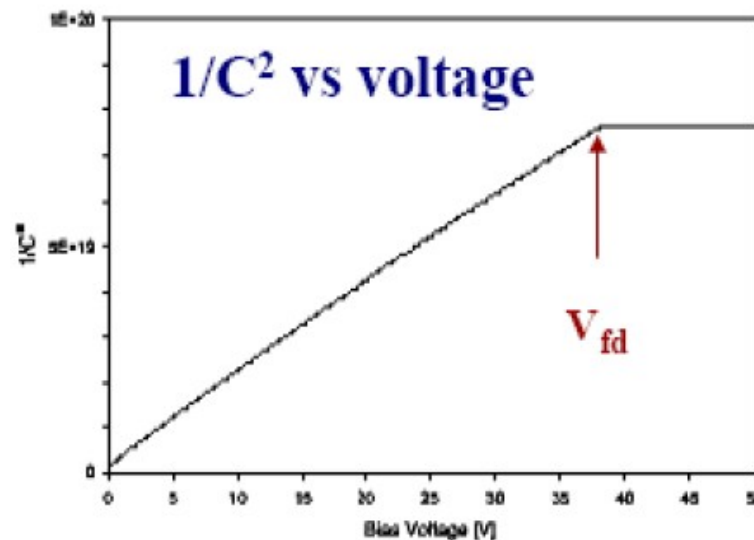
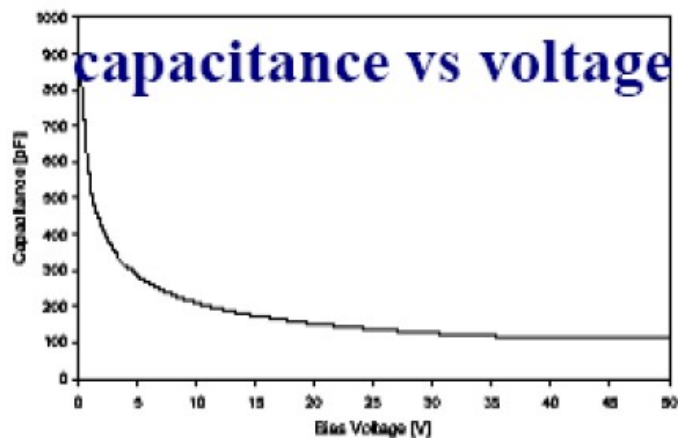
- **Very simple structures in order to concentrate on the bulk features**
  - Typical thickness: 300µm
  - Typical active area: 0.5 × 0.5 cm<sup>2</sup>
- **Openings in front and back contact**
  - optical experiments with lasers or LED

- The depletion voltage can be determined by measuring the capacitance versus the applied reverse bias voltage. The capacitance is simply the parallel plate capacity of the depletion zone.



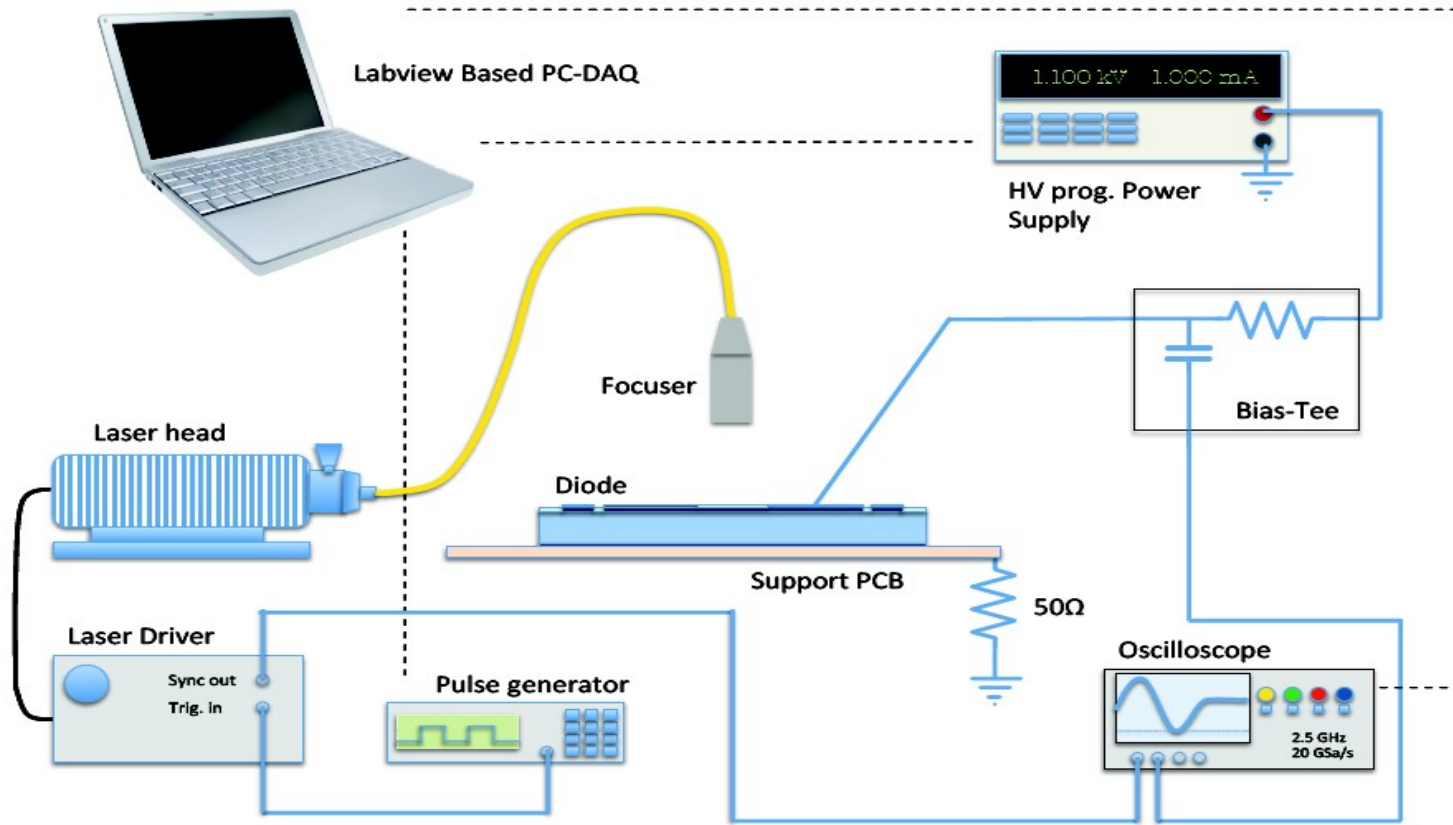
$$C(V) = \frac{\epsilon\epsilon_0 A}{w} = A \cdot \sqrt{\frac{\epsilon\epsilon_0 q_0 |N_{eff}|}{2 \cdot V}}$$

- $\epsilon, \epsilon_0$  dielectric constants
- $A$  = area of sensor
- $w$  = depletion width
- $N_{eff}$  = effective doping concentration
- $V$  = Voltage applied
- $q_0$  = elementary charge



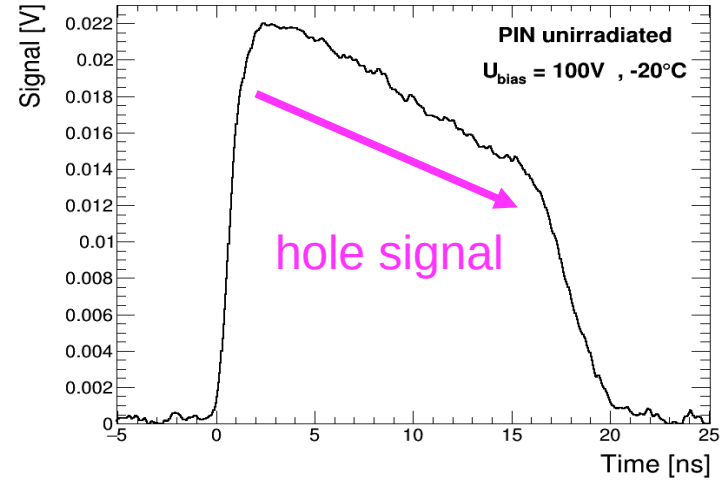
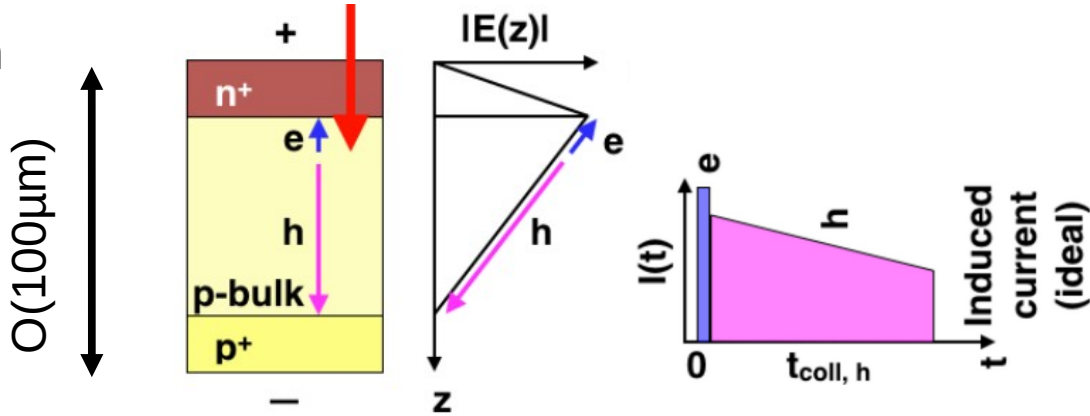
$$V_{dep} = \frac{q_0}{2\epsilon\epsilon_0} |N_{eff}| d^2$$

- Study of laser pulse induced current transients in silicon sensors
  - Schematic view of the TCT setup

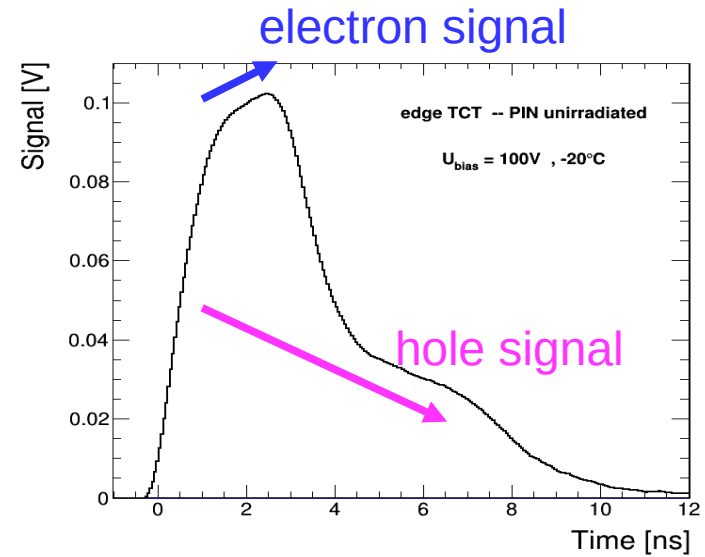
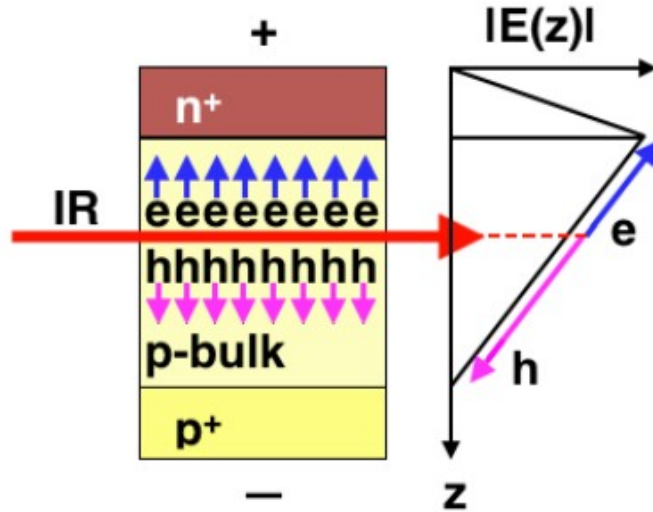


# TCT explained

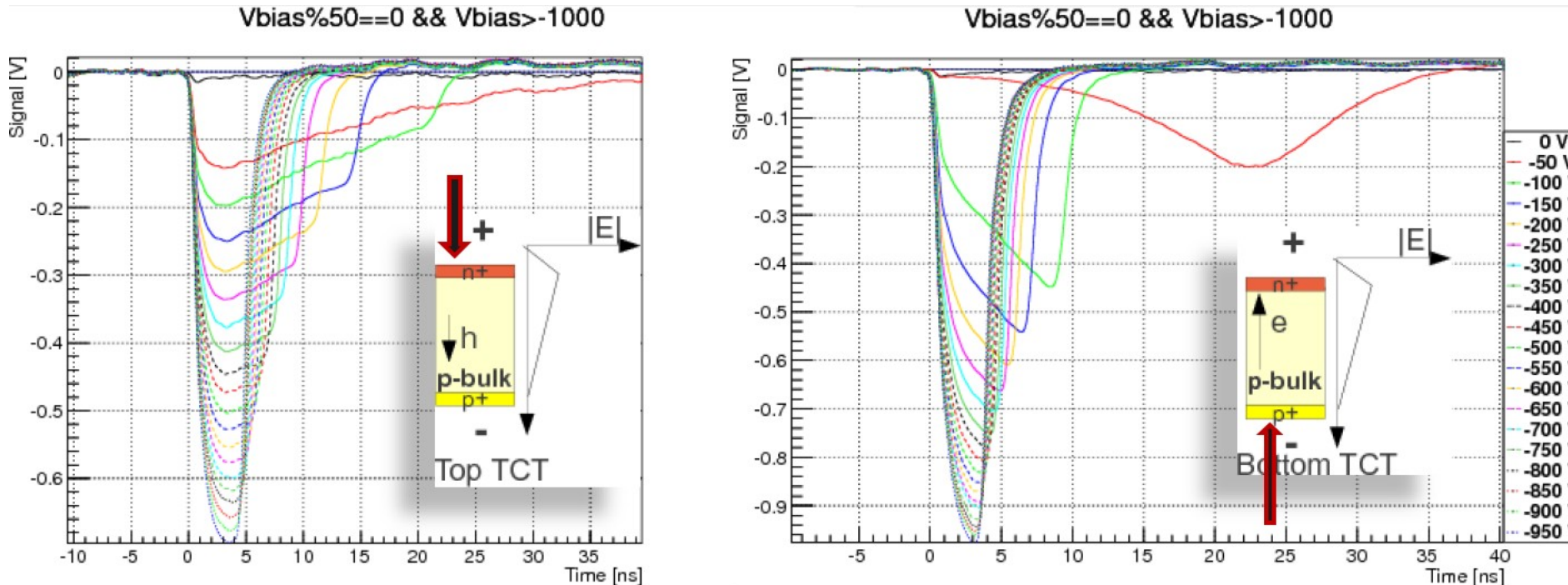
Red 660nm



Near IR 1064nm  
edge-TCT



DT seminar: M. Fernández, The Transient Current Technique: laser characterization of silicon detectors <https://indico.cern.ch/event/684193/>  
C. Gallrapp, The TCT+ setup - a system for TCT, eTCT and timing measurements, 1st TCT Workshop (2015)



- Top TCT, h-injection (p-bulk):

- Induced current maximum at front junction
- Longer collection time due to smaller drift velocity

- Bottom TCT, e-injection:

- Drift velocity increase towards the front side
- Shorter collection time, and higher amplitude of pulses, both due to higher drift velocity

- **Silicon Sensors are based on reverse biased pn-junctions** (silicon sensors are reverse biased diodes)
- **Silicon Detectors at the LHC and upgrade of LHC**
  - Inner tracking at LHC and HL-LHC done by silicon detectors
  - Hybrid-pixel (planar and 3D) and strip sensors implemented in LHC experiments (ALICE upgraded to monolithic sensors)
  - Radiation Hard Monolithic sensors under development (competing beyond LS3 for HL-LHC upgrades)
- **Radiation Damage in Silicon Sensors**
  - Damage: displacement damage that is evidenced as defect levels in the band gap of the semiconductor  
(+ some impact of surface damage in segmented sensors)
  - **Modification of internal electric field** (space charge distribution, depletion voltage, “type inversion”, reverse annealing, loss of active volume, ...), defect engineering possible!
  - **Increase of Leakage Current** and **Charge Trapping** (same for all silicon materials)
  - **Signal to Noise ratio** is quantity to watch (material + geometry + electronics)
- **Radiation tolerant silicon sensors**
  - Several examples of successful Material and Device Engineering (mitigation strategies)  
oxygenation, 3D sensors, p-type (n-readout) sensors
- **Hands-on:**
  - **Current-Voltage and Capacitance-Voltage measurements**
  - **Transient Current Technique (TCT) measurements**

- **Most references to particular works given on the slides**

- RD50 workshop presentations: <http://www.cern.ch/rd50/>
- Conferences: VERTEX, PIXEL, RESMDD, ...

- **Instrumentation Schools**

- ICFA, EDIT, ESI, CERN & DESY Summer Student Lectures

- **Books about silicon tracking detectors (and radiation damage)**

- Helmuth Spieler, “Semiconductor Detector Systems”, Oxford University Press 2005
- C.Leroy, P-G.Rancoita, “Silicon Solid State Devices and Radiation Detection”, World Scientific 2012
- Frank Hartmann, “Evolution of silicon sensor technology in particle physics”, Springer 2009 & 2017
- L.Rossi, P.Fischer, T.Rohe, N.Wermes “Pixel Detectors”, Springer, 2006
- Gerhard Lutz, “Semiconductor radiation detectors”, Springer 1999

- **Review Articles**

- 2018: Garcia-Sciveres and Wermes, A review of advances in pixel detectors for experiments with high rate and radiation, <https://doi.org/10.1088/1361-6633/aab064>
- 2018: M.Moll, Displacement Damage in Silicon Detectors for High Energy Physics <https://doi.org/10.1109/TNS.2018.2819506>

- **Research collaborations and web sites**

- CERN RD50 collaboration (<http://www.cern.ch/rd50> ) - Radiation Tolerant Silicon Sensors
- CERN RD42 collaboration – Diamond detectors
- Inter-Experiment Working Group on Radiation Damage in Silicon Detectors (CERN)
- ATLAS IBL, ATLAS and CMS upgrade groups